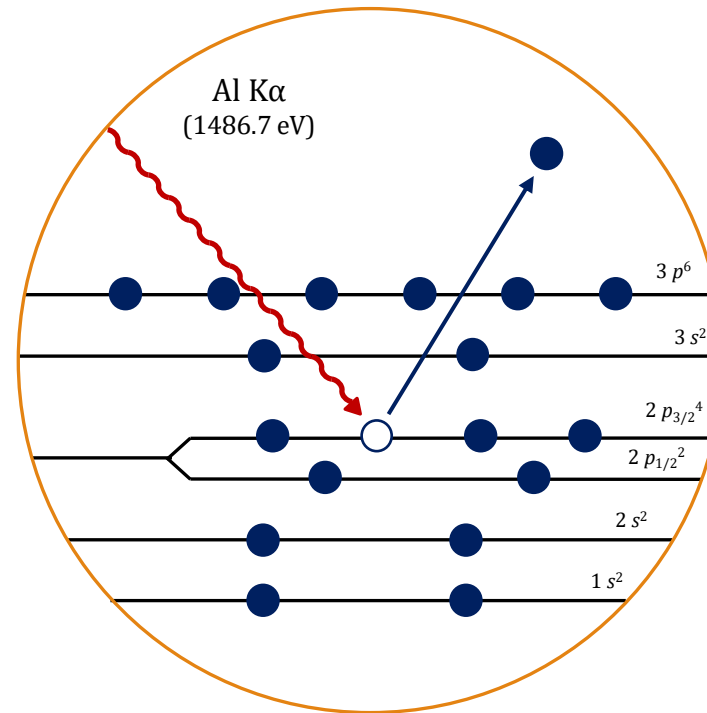


X-Ray Photoelectron Spectroscopy



XPS

X-Ray Photoelectron Spectroscopy

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4. Technical issues & Auxiliary features
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 2. Ion beam sputtering & depth profiling
 3. Angle resolved XPS
 4. Small area analysis and imaging

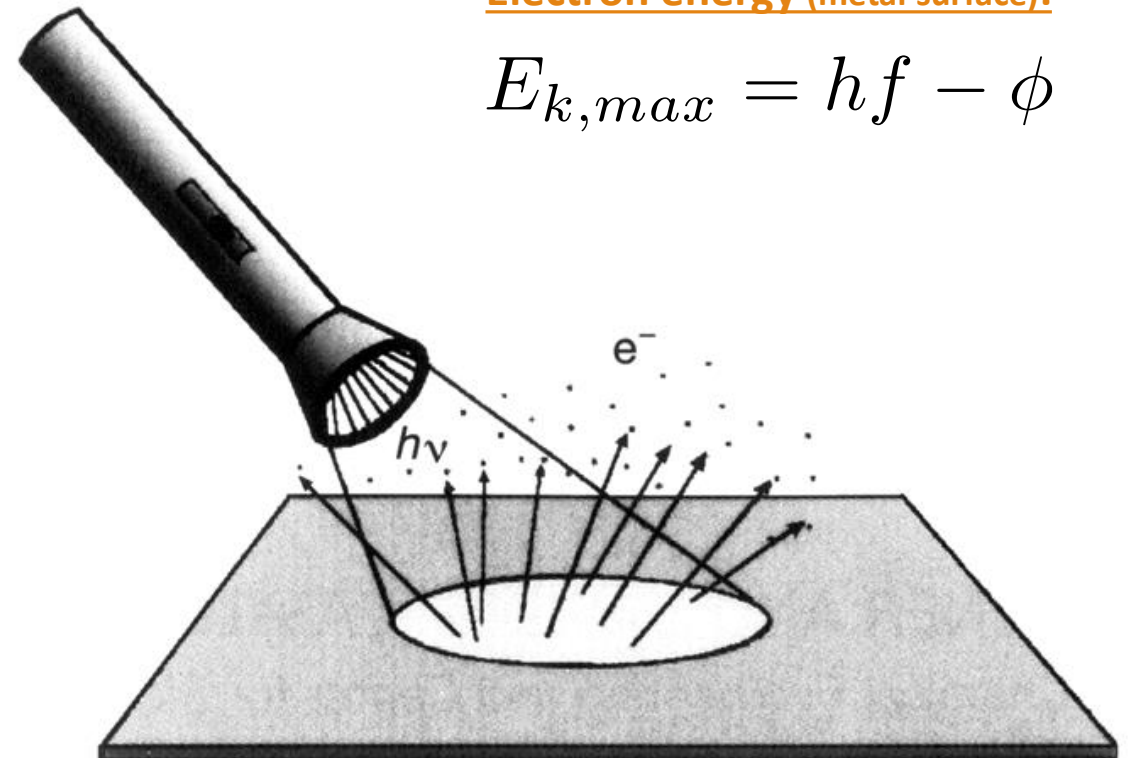
The photoelectric effect

Emission of electrons when light is shone onto a material:

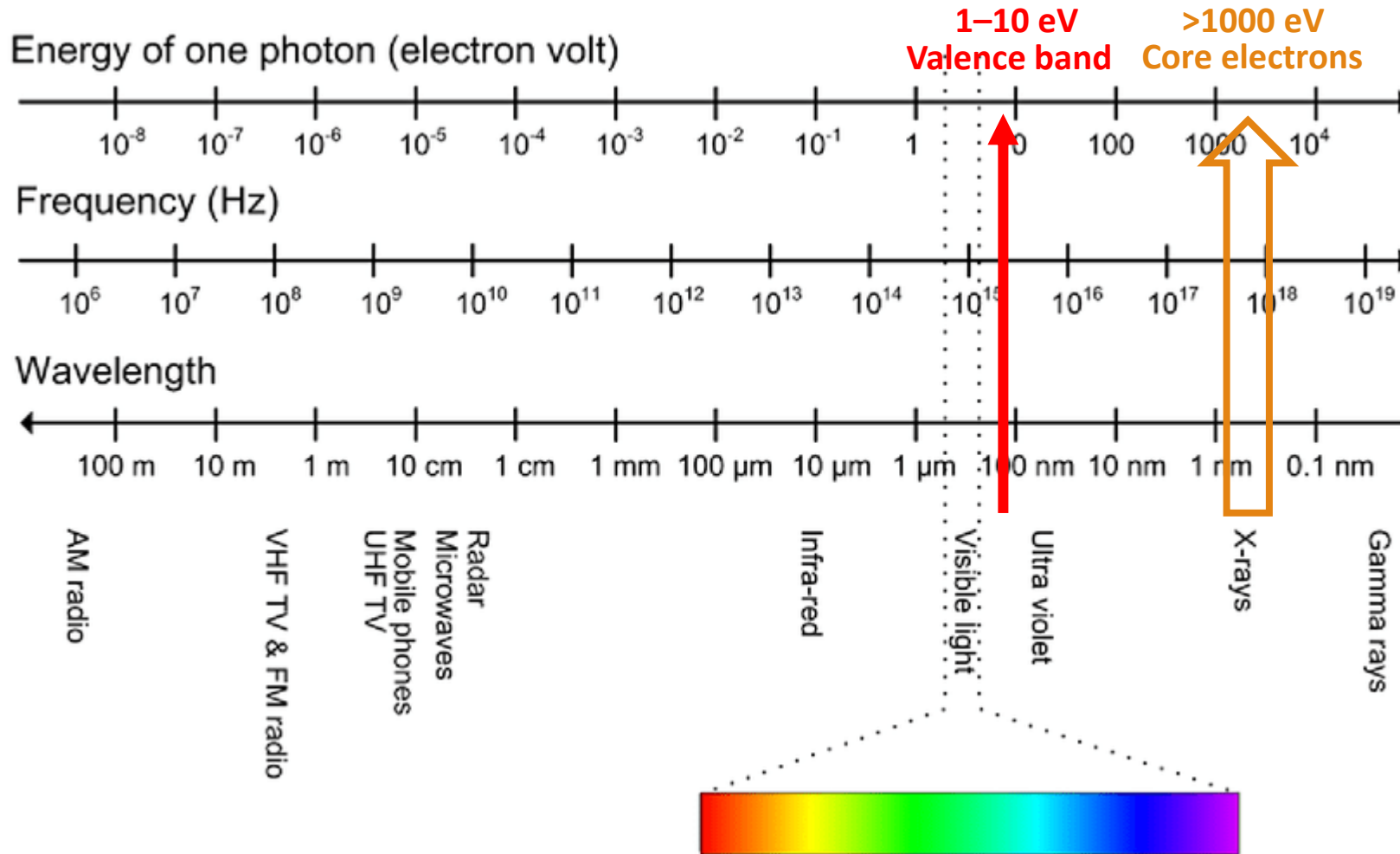
- Photoelectrons
- Metal plate irradiated by UV light emits charged particles: H. Hertz, 1887
- Shown to be electrons: J. J. Thomson, 1899
- Theory on photon quanta: A. Einstein, 1905
- Verified through experiments: R. Millikan, 1915

Electron energy (metal surface):

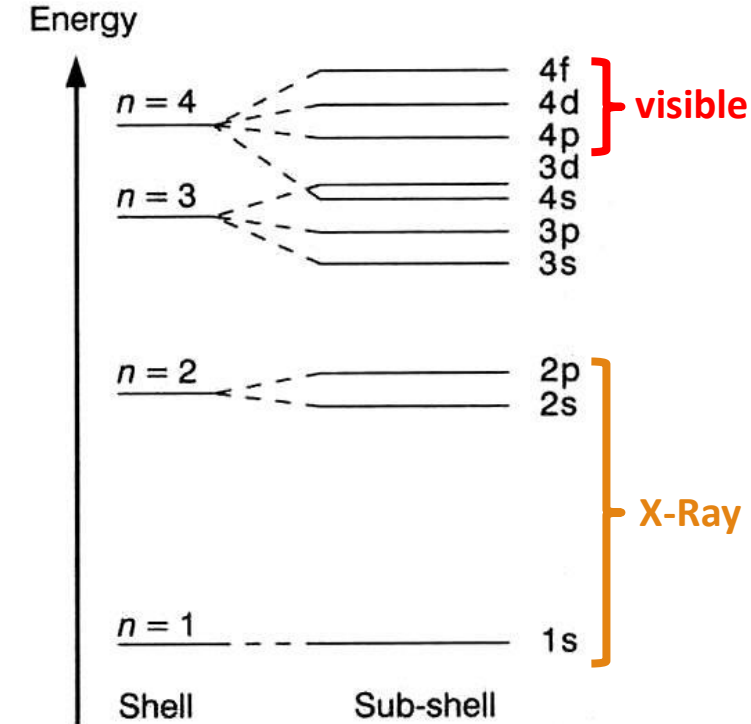
$$E_{k,max} = hf - \phi$$



The electromagnetic spectrum



Electron energy levels:



- Core levels have larger differences in energy!

Photoemission as an analytical tool

Electron Spectroscopy for Chemical Analysis (ESCA)

- Kai Siegbahn, 1957 (Nobel Prize 1981)

Widely used technique for surface analysis:

- **XPS**: X-Ray Photoelectron Spectroscopy
- **ESCA**: Electron Spectroscopy for Chemical Analysis
- **UPS**: Ultraviolet Photoelectron Spectroscopy
- **PES**: Photoemission Spectroscopy

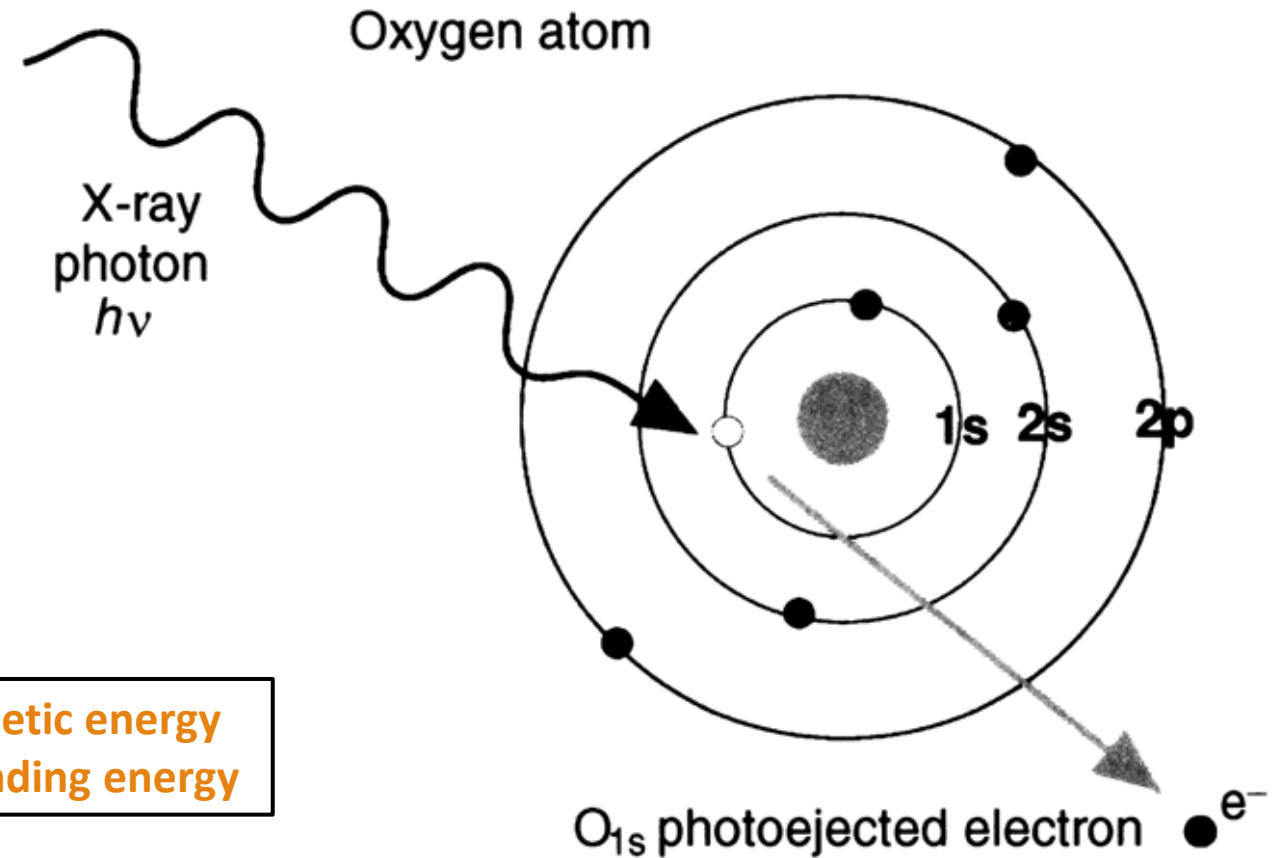
Requirement:

- Monochromatic & High energy photon source

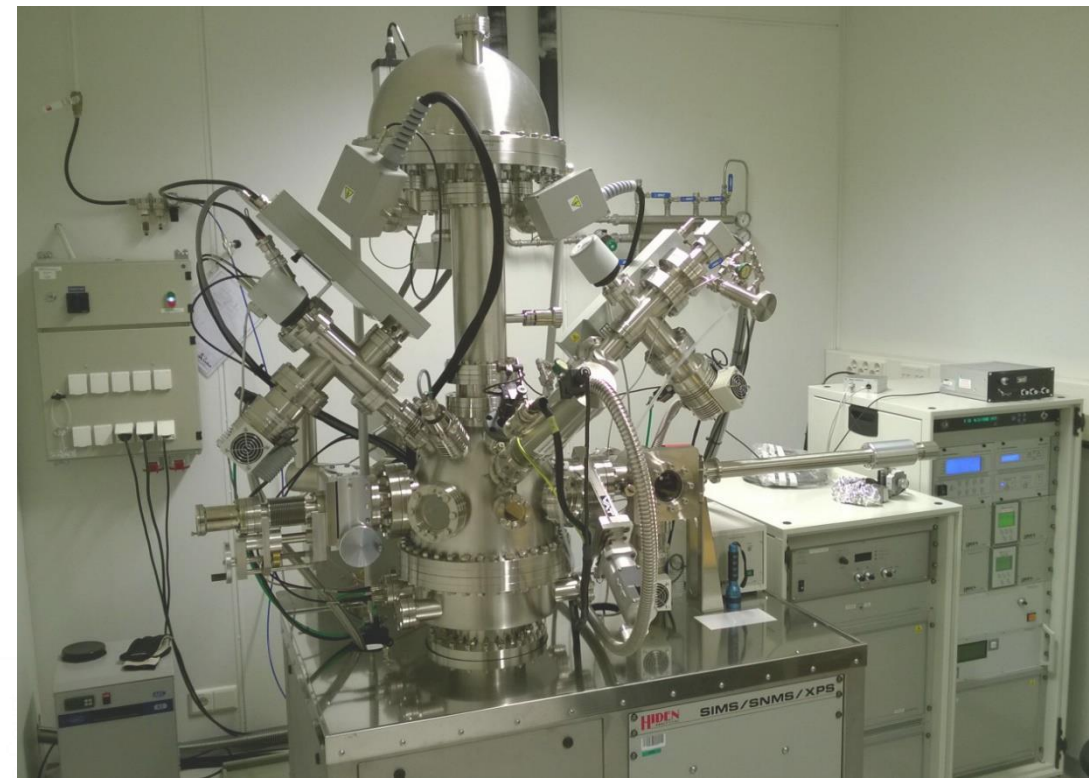
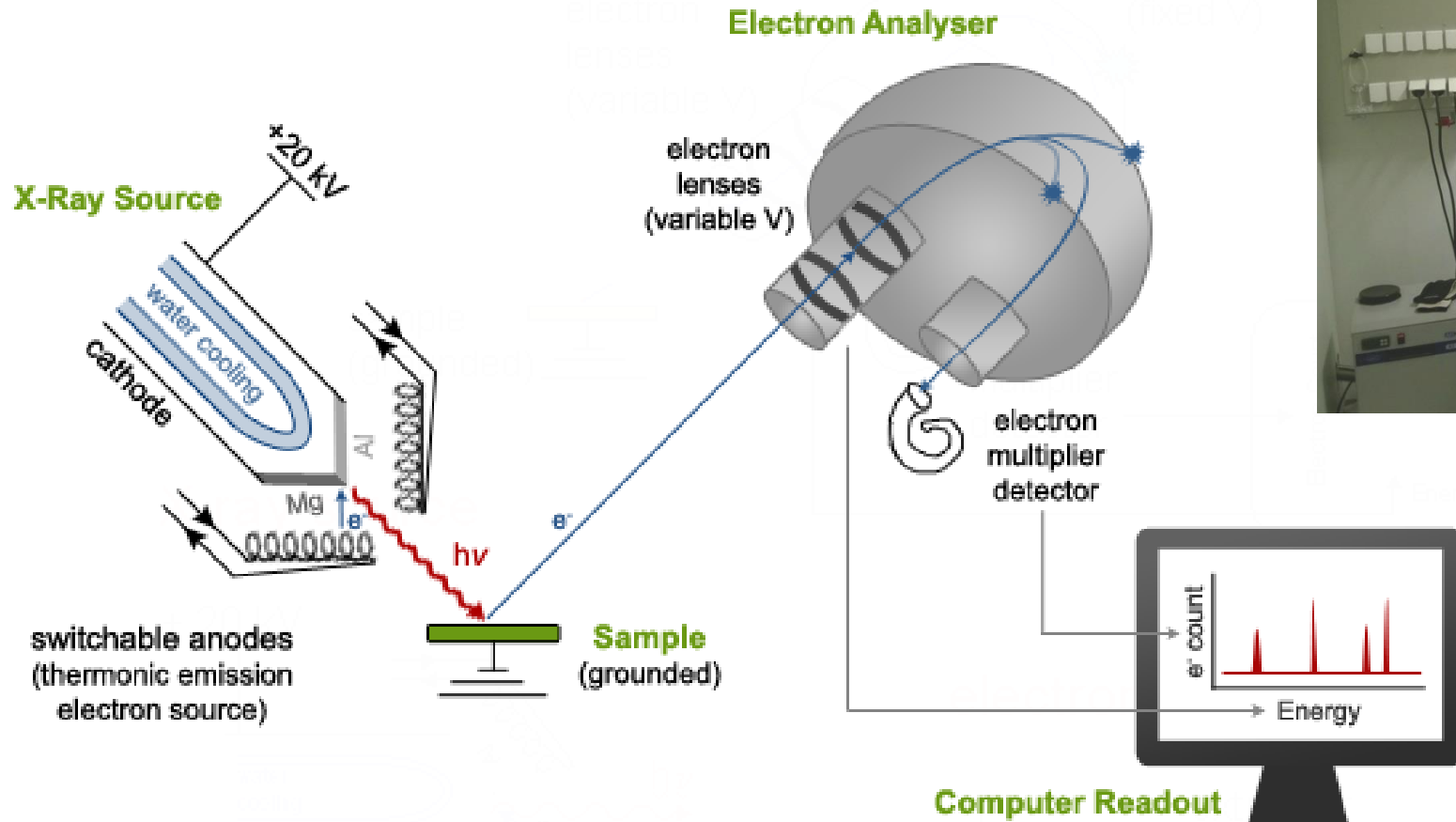
Electron energy (any surface):

$$E_k = hf - E_b + \phi$$

E_k = kinetic energy
 E_b = binding energy



Instrumentation

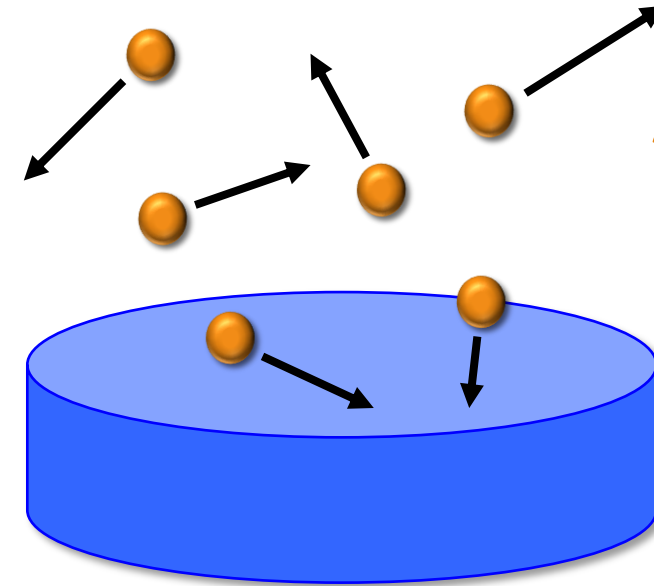


- X-ray source (typically Mg or Al anode)
- Electron energy analyzer
- Electronics & computer system
- Vacuum system (ultra-high vacuum)
- Extras:
 - Ion gun for etching (argon ions)
 - Neutralizer (flood gun, non-conductive samples)
 - Cooling system (lots of heat from X-ray source)

Degree of vacuum

Improved vacuum:

- Increases the mean free path for photons and electrons
- Removes adsorbed gases from the sample
- Eliminates adsorption of contaminants on sample surface



Absorption rate:

$$R = \frac{p}{\sqrt{2\pi M k T}}$$

Low vacuum	$10^3 - 10^0$ mbar
Medium vacuum	$10^0 - 10^{-3}$ mbar
High vacuum	$10^{-3} - 10^{-6}$ mbar
Very high vacuum	$10^{-6} - 10^{-9}$ mbar
Ultra-high vacuum	$10^{-9} - 10^{-12}$ mbar

Example:

- $p = 10^{-6}$ mbar

- O_2 ($M=32$)

- $T = 300$ K

- $k = 1.381 \cdot 10^{-23}$ J/K

$$\longrightarrow R = 4.7 \cdot 10^{14} \frac{1}{\text{cm}^2 \text{s}}$$

Complete coverage: $1\text{ML} \sim 1 \cdot 10^{15}$ atoms/cm²

- Surface will be clean for about 1 second...

AXIS 165 / AXIS Ultra^{DLD}

at Aalto CHEM 1995-2021 (L-S Johansson)

- Analysis on > 200 samples / year

Cellulosic materials (ca 50 % of samples):

- Pulps surface analysis & process evaluations
- Paper coatings, contamination, fundamentals
- Model surfaces, mono/multicomponent film formation, and reaction dynamics
- Cellulose nanofibrils, whiskers & bacterial cellulose, fundamentals & applications
- Wood hydrothermal modification, adhesion
- Derivatives: TEMPO, click, CMC, silylation...
- Functional surfaces: bio-interfaces, biological surfaces, biomimetic materials
- Composites of cellulose and derivatives: polymers, clay, lignin, chitosan, graphene, CNTs
- Textiles: flax, cotton, MMC, synthetic fibers
- Carburized celluloses: e.g. catalysis

Other materials (50 % samples):

- Ultra-thin inorganic and organic films: ALD deposited, spin-coated, LB films, CVD, plasma, graphenes, CNTs, DLCs
- Surface analysis of metals, alloys, oxides, composites, polymers, powders, fibers, deposits
- Contamination analyses: e.g. semiconductor devices, quality control



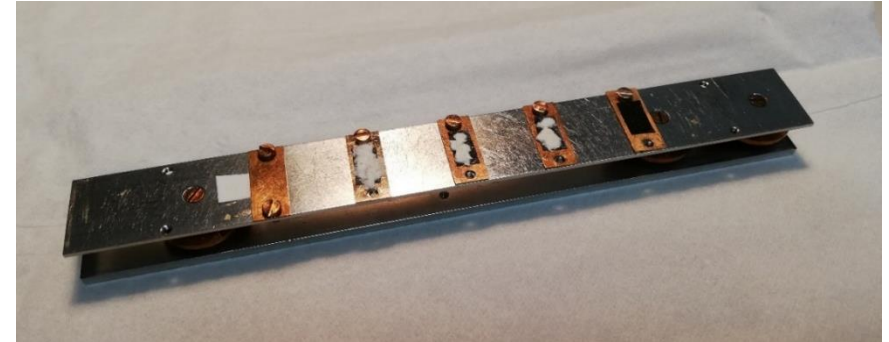
XPS in applied surface science

Quantification of elements at the surface of materials:

- Detection of all elements (except for hydrogen and helium)
- Chemical identification
- Surface distribution of elements (such as films vs islands)
- Easy sample preparation
- Non-destructive (no particle bombardment, only soft X-rays)

Limitations:

- XPS can only analyze the outermost surface layers (0-10 nm)
- It will not tell you the average bulk composition
- Surface contamination is a big issue
- Samples must tolerate Ultra High Vacuum ($<10^{-9}$ mbar)



Samples:

- Almost any type of solid sample : Wafers, powders, fibers, composites, organic/biological specimens, etc.
- Allows for insulating, conducting or heterogeneous materials.
- Sample preparation: **As little as possible.**
- Secured on holder with springs or UHV-tape.

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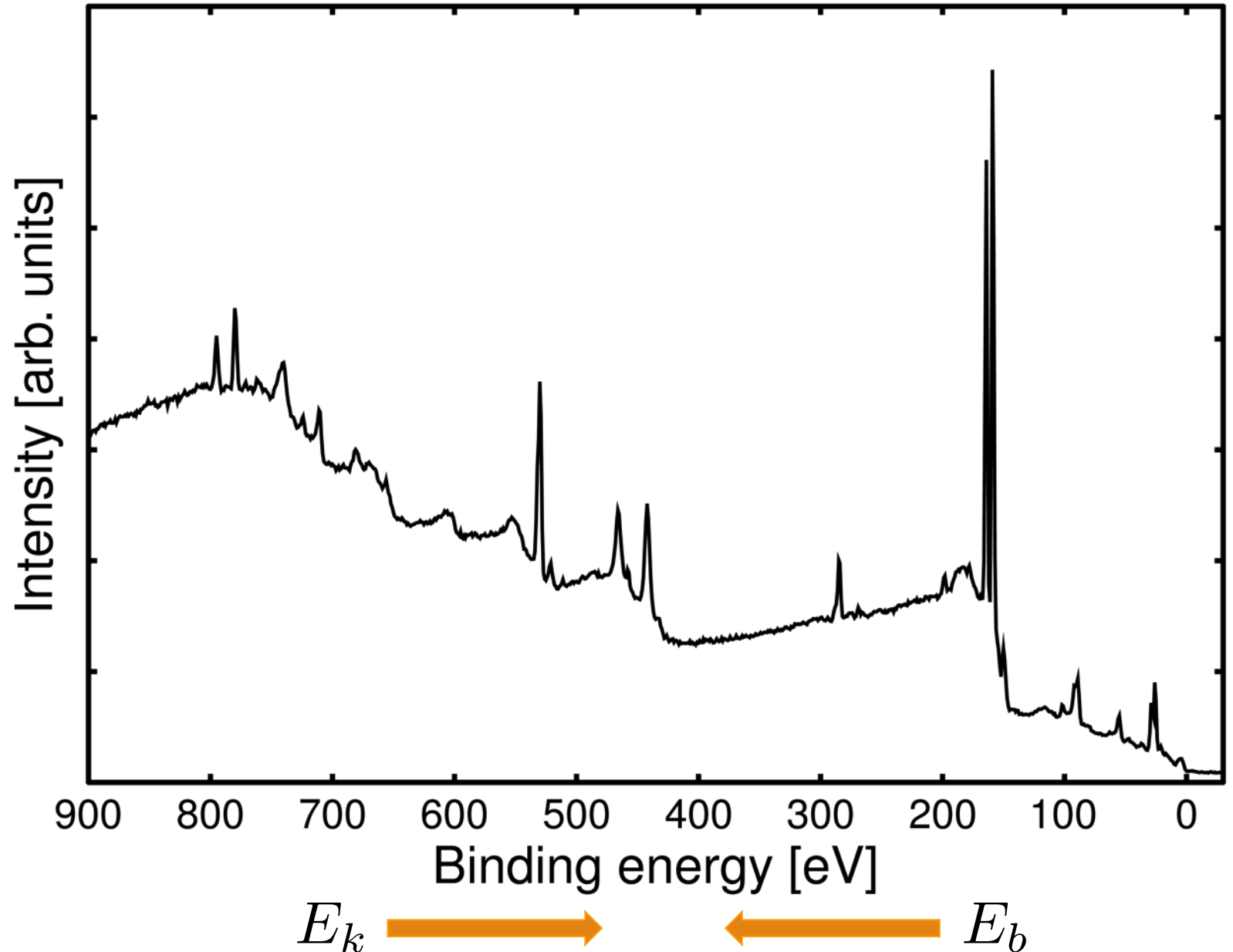
Experiment

Measurement:

- Retarding potential is step-wise decreased
- Dwell time for each step: a few 100 ms
- Number of electrons measured for each energy

Results:

- Photoemission spectrum
- High intensity peaks at core level binding energies
- **Survey spectra** – large range, low resolution
- **High-resolution spectra** – small range, high resolution



Binding energies

Core level energies are specific for each element:

- Each peak in the survey spectrum can be assigned to the binding energy of electrons from a specific energy level and element

Identification:

- Start with the strongest peaks – find energy level that matches (C 1s, O 1s + Auger lines are usually present)
- Compare other energy levels in element with spectrum – assign peaks
- Usually **fixed ratios** between **peak heights** for same element
- If there is a strong peak, but the other lines for that element do not appear – try to find another element!

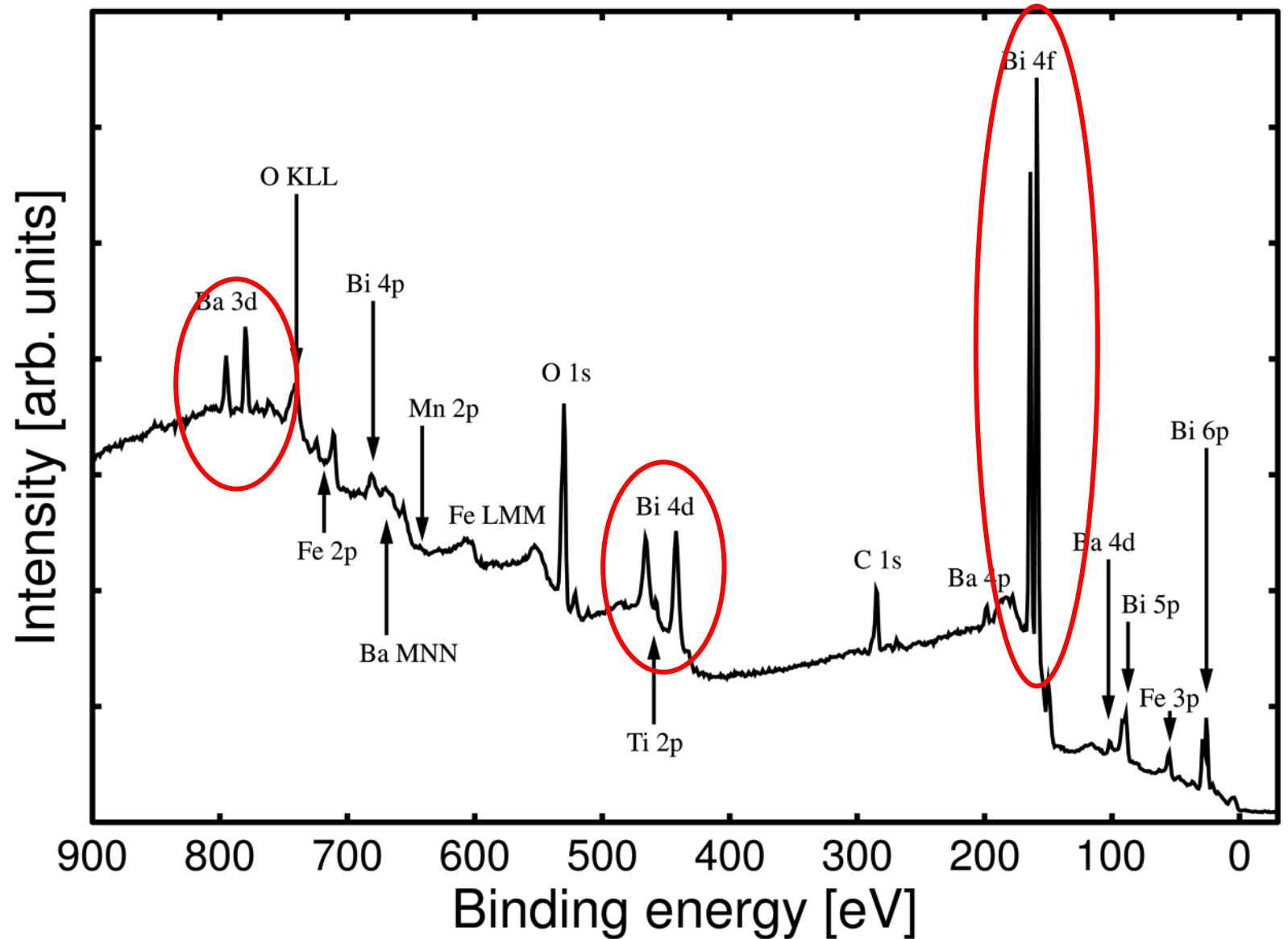
Table 4.2. Binding energies of some elements

Z	El	1s _{1/2} K	2s _{1/2} L ₁	2p _{1/2} L ₂	2p _{3/2} L ₃	3s _{1/2} M ₁	3p _{1/2} M ₂	3p _{3/2} M ₃	3d _{3/2} M ₄	3d _{5/2} M ₅
1	H	14								
2	He	25								
3	Li	55								
4	Be	111								
5	B	188			5					
6	C	284			6					
7	N	399			9					
8	O	532	24		7					
9	F	686	31		9					
10	Ne	867	45		18					
11	Na	1072	63		31	1				
12	Mg	1305	89		52	2				
13	Al	1560	118	74	73	1				
14	Si	1839	149	100	99	8				
15	P	2149	189	136	135	16	10			
16	S	2472	229	165	164	16	8			
17	Cl	2823	270	202	200	18	7			
18	Ar	3202	320	247	245	25	12			
19	K	3608	377	297	294	34	18			
20	Ca	4038	438	350	347	44	26			5
21	Sc	4493	500	407	402	54	32			7
22	Ti	4965	564	461	455	59	34			3
23	V	5465	628	520	513	66	38			2
24	Cr	5989	695	584	757	74	43			2
25	Mn	6539	769	652	641	84	49			4
26	Fe	7114	846	723	710	95	56			6
27	Co	7709	926	794	779	101	60			3
28	Ni	8333	1008	872	855	112	68			4
29	Cu	8979	1096	951	932	120	74			2
30	Zn	9659	1194	1044	1021	137	90			9
31	Ga	10367	1299	1144	1117	160	106			20
42	Mo	20000	2866	2625	2520	505	410	393	208	205
46	Pd	24350	36304	3330	3173	670	559	531	340	335
48	Ag	25514	3806	3523	3351	718	602	571	373	367
73	Ta*	67416	11681	11136	11544	*566	*464	*403	*24	*22
79	Au*	80724	14352	13733	14208	*763	*643	*547	*88	*84

* 4s, 4p et 4f levels indicated, respectively

Survey

- Peaks can now be labeled
- When all peaks are accounted for, elemental constituents have been found
- Some features are not necessarily discrete peaks from core level electrons:
 - Double peaks
 - Broad peaks in bunches
 - Etc...



Spin-orbit splitting

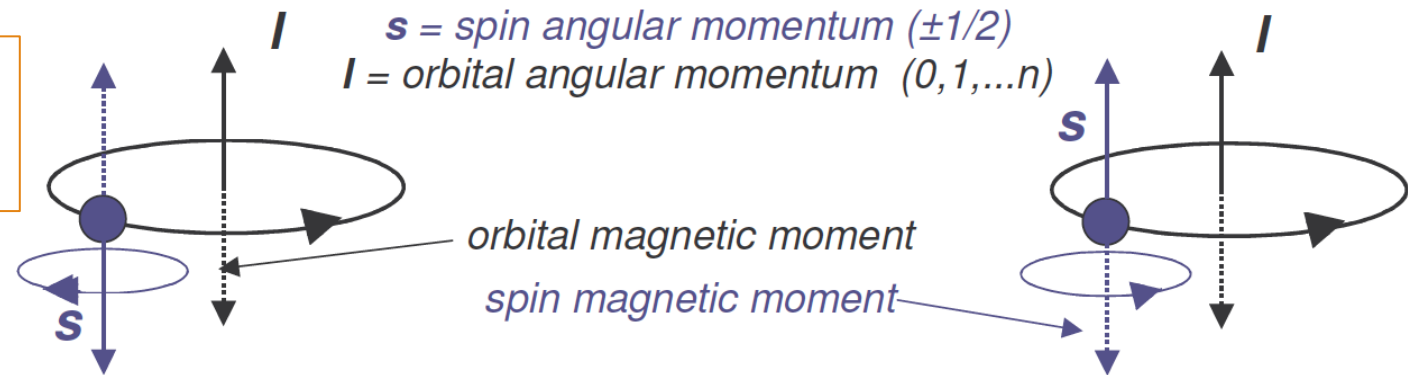
Before ionization

- Inner shells are filled
- No spin-orbit interactions

Antiparallel spins
 $j = l - s$
 Higher E_b

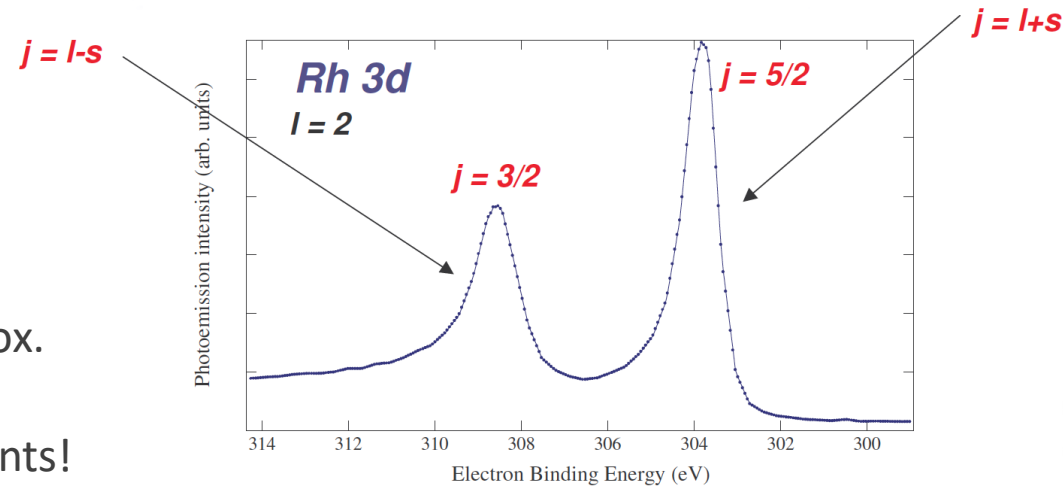
After ionization

- Un-paired electrons in inner shells
- Spin-orbit coupling
 - Interaction between magnetic moments from electron spin and orbit affects final energies

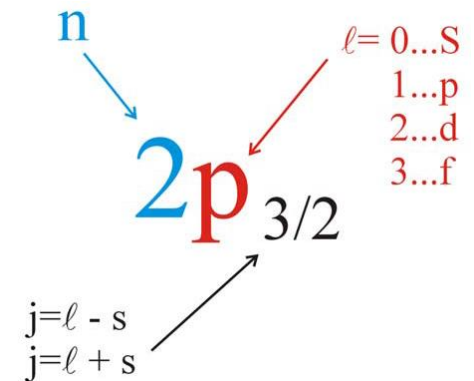


Spin-orbit splitting results in the formation of **doublets**:

- Fixed **intensity ratios** between peaks
- For the same element ΔE_b will be approx. constant in different compounds
- Can be used for identification of elements!

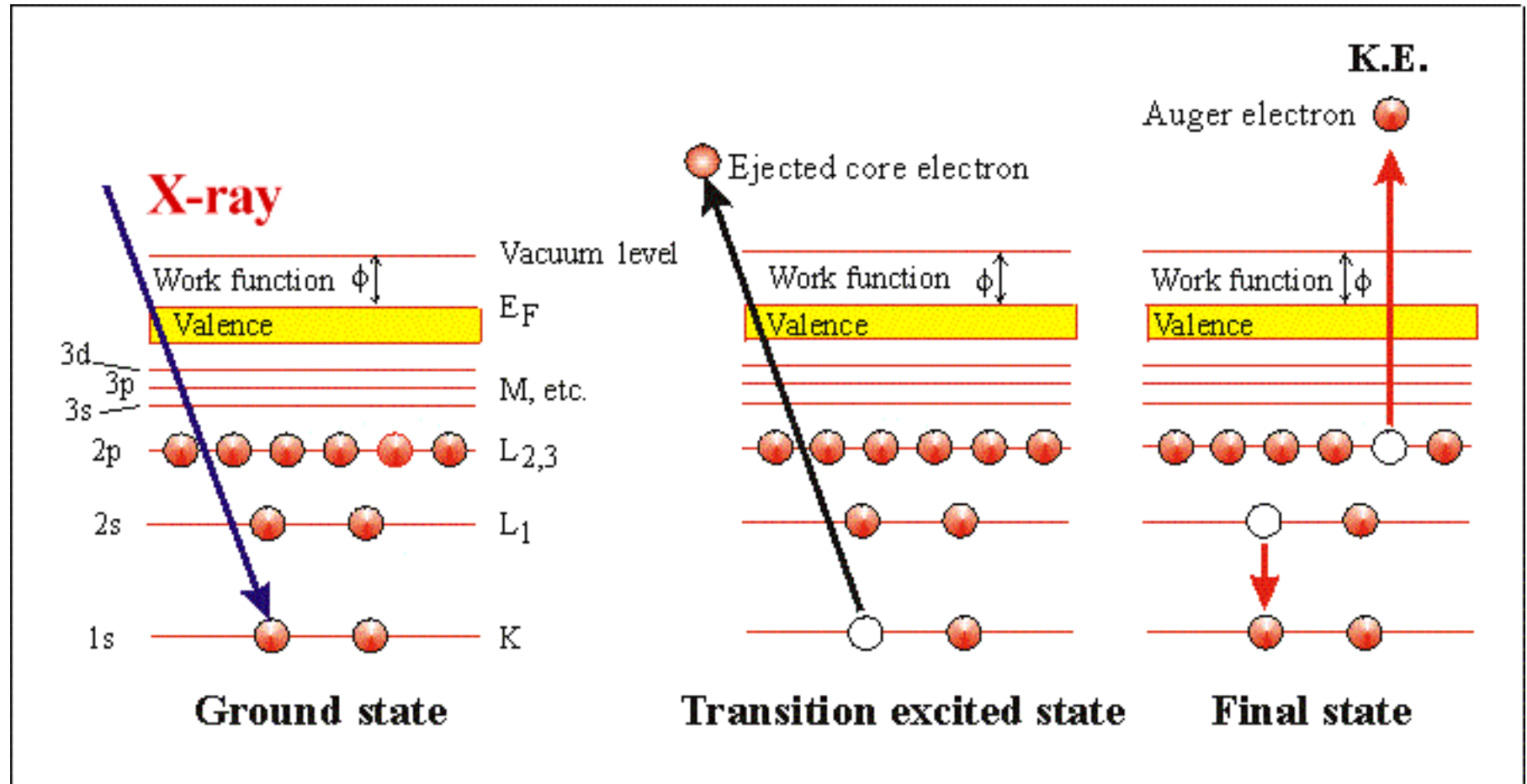


Peak labeling:



Auger electrons

- Atoms are in transitional excited states after core electrons are ejected
- Auger electrons can be emitted when excited states are relaxed
- E_k is independent of X-ray photon energy
- Position in E_b scale will depend on X-ray source



Characteristic X-rays

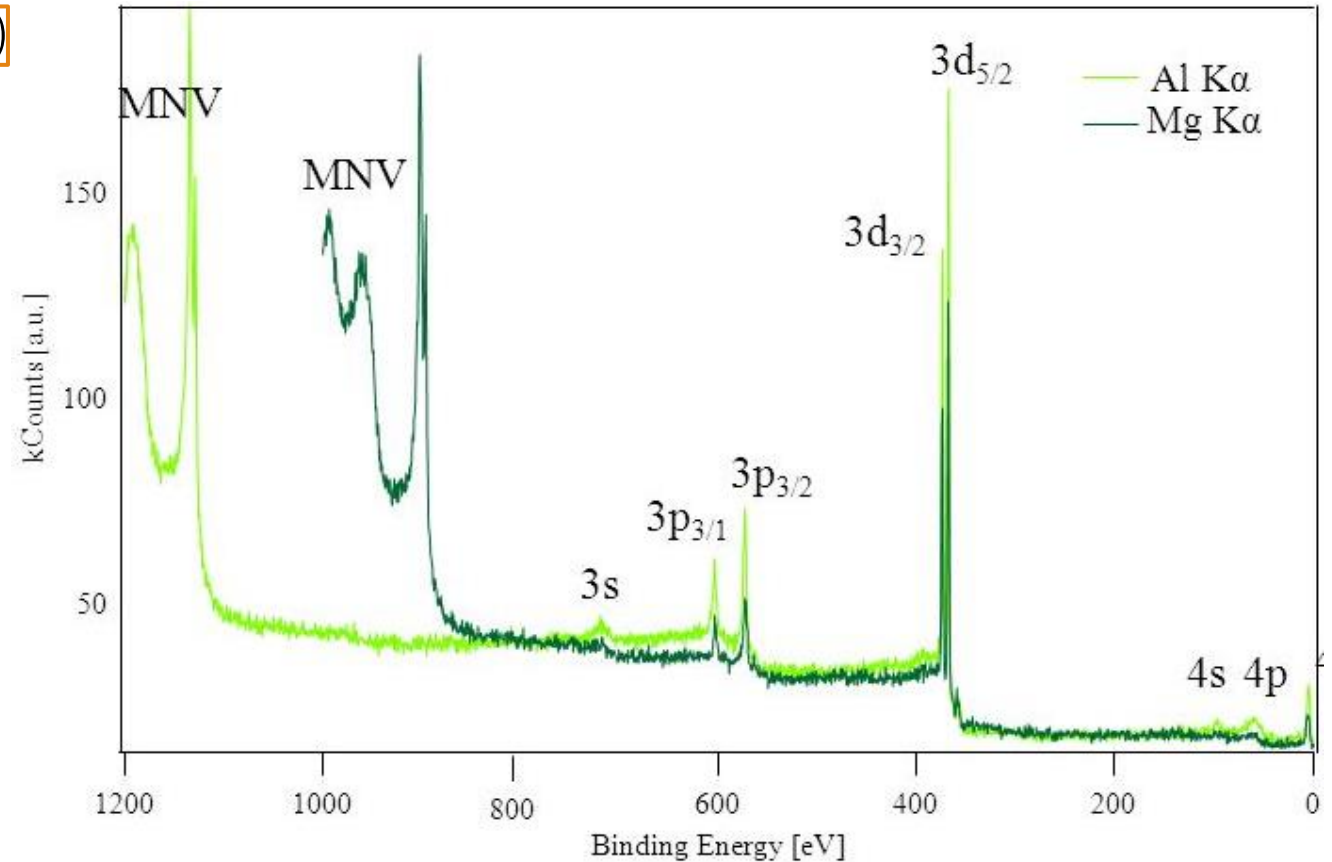
Different X-rays:

- Binding energy constant $E_k = hf - (E_b + \phi)$
- Kinetic energy for Auger electrons constant:
 - Auger transition (“binding”) energy varies

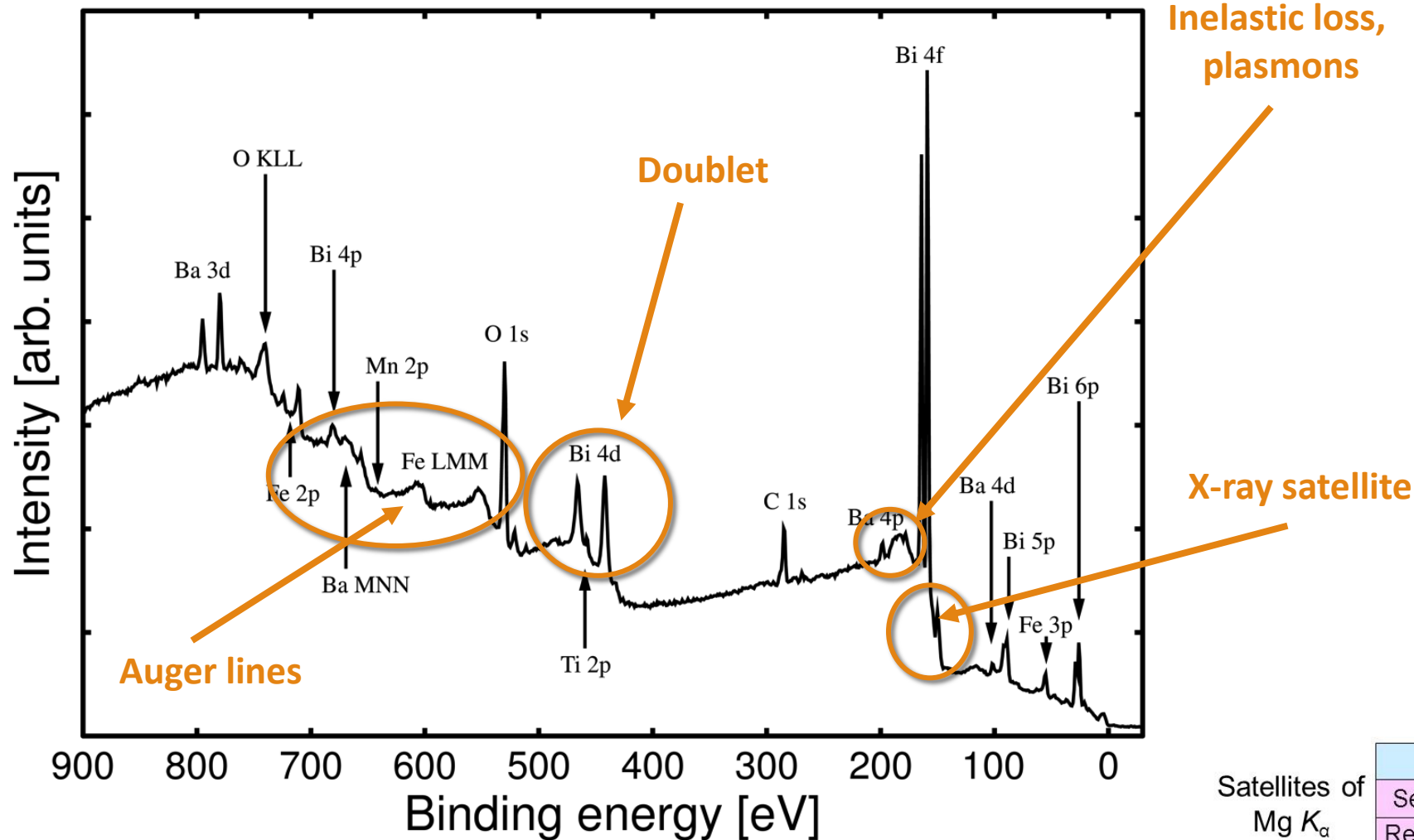
Line	Energy (eV)	Width (eV)
Y M_{ζ}	132.3	0.47
Zr M_{ζ}	151.4	0.77
Cr L_{α}	572.8	3.0
Cu L_{α}	929.7	3.8
Mg K_{α}	1253.6	0.7
Al K_{α}	1486.6	0.85
Si K_{α}	1739.5	1.0
Cu K_{α}	8048.0	2.6



Typical Ag spectra:



Other features



Intrinsic loss features:

- **“Shake-up” satellites**
- Finite probability that the ion formed in the photoemission process will be excited – lower E_k

Extrinsic loss features:

- **Plasmons**
- Photoelectrons travelling in a solid will interact with other electrons – lower E_k

X-ray effects:

- **Satellites**
- Minor X-ray components from anode material – higher $E_0=hf$
- **Ghosts**
- X-rays from other elements (very rare)

Satellites of Mg K_α

Line	α_{12}	α_3	α_4	α_5	α_6	β
Separation (eV)	0.0	8.4	10.2	17.5	20	48.5
Relative Intensity	100	8.0	4.1	0.55	0.45	0.5

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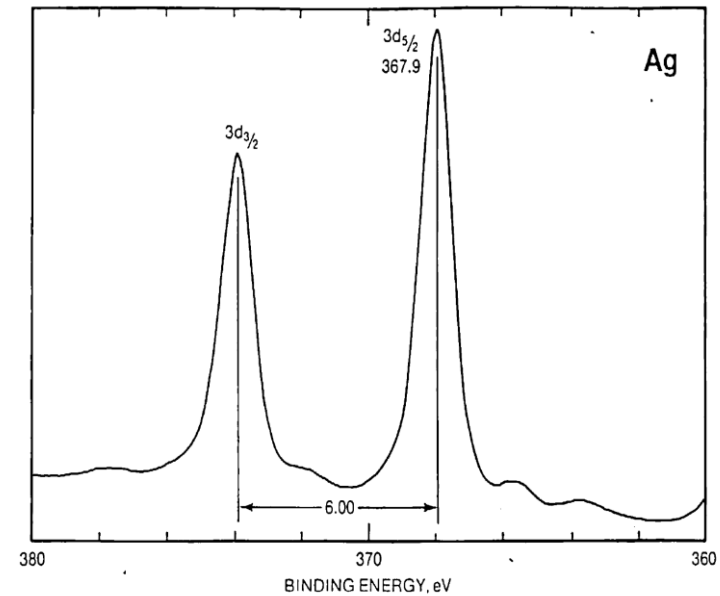
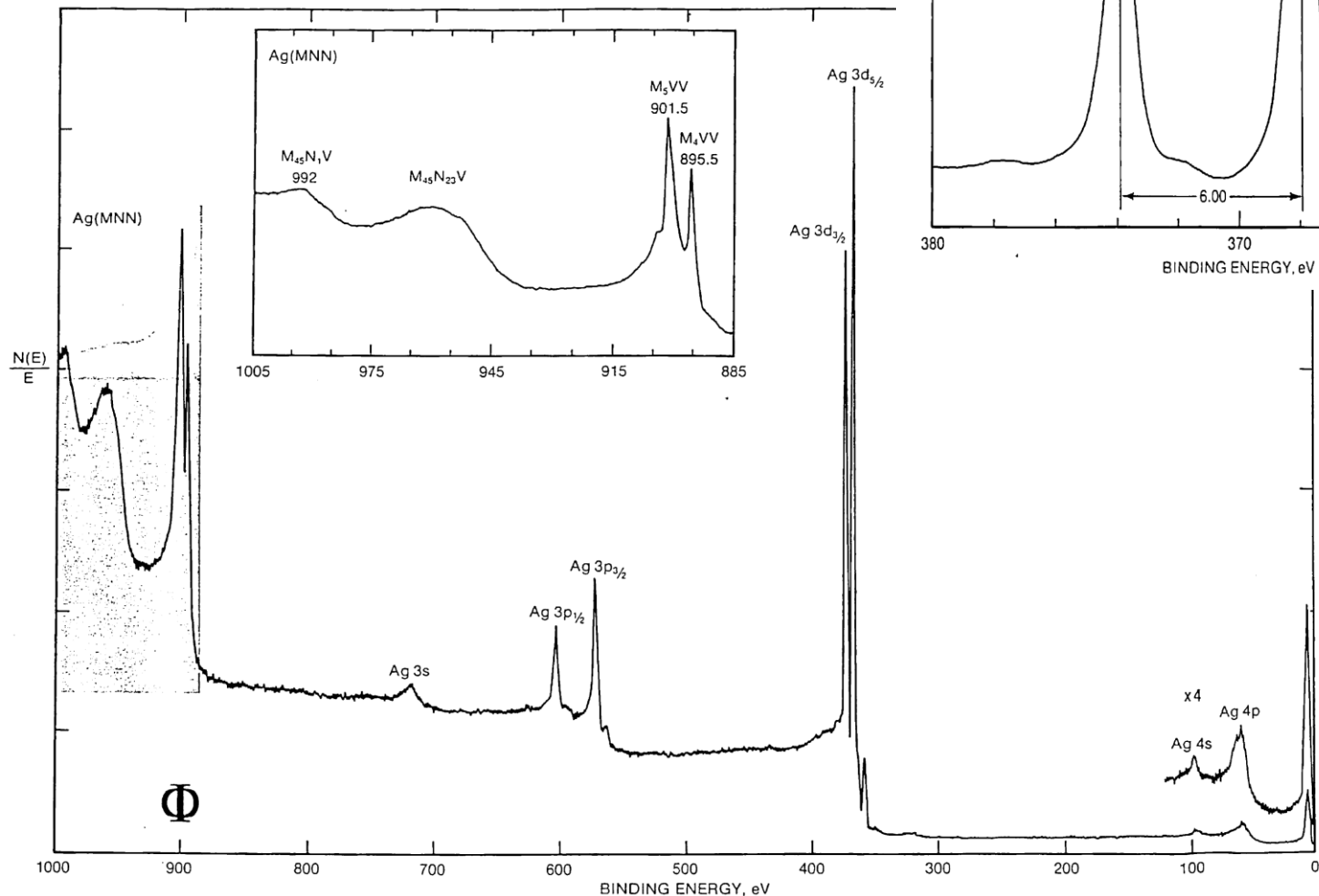
Reference spectra

HANDBOOK OF X-RAY PHOTOELECTRON SPECTROSCOPY

A Reference Book of Standard Data
For Use In
X-Ray Photoelectron Spectroscopy

Handbooks with reference
data:

- Vital for identification of elements
- Reference survey and high-resolution spectra



Survey spectra: example 1

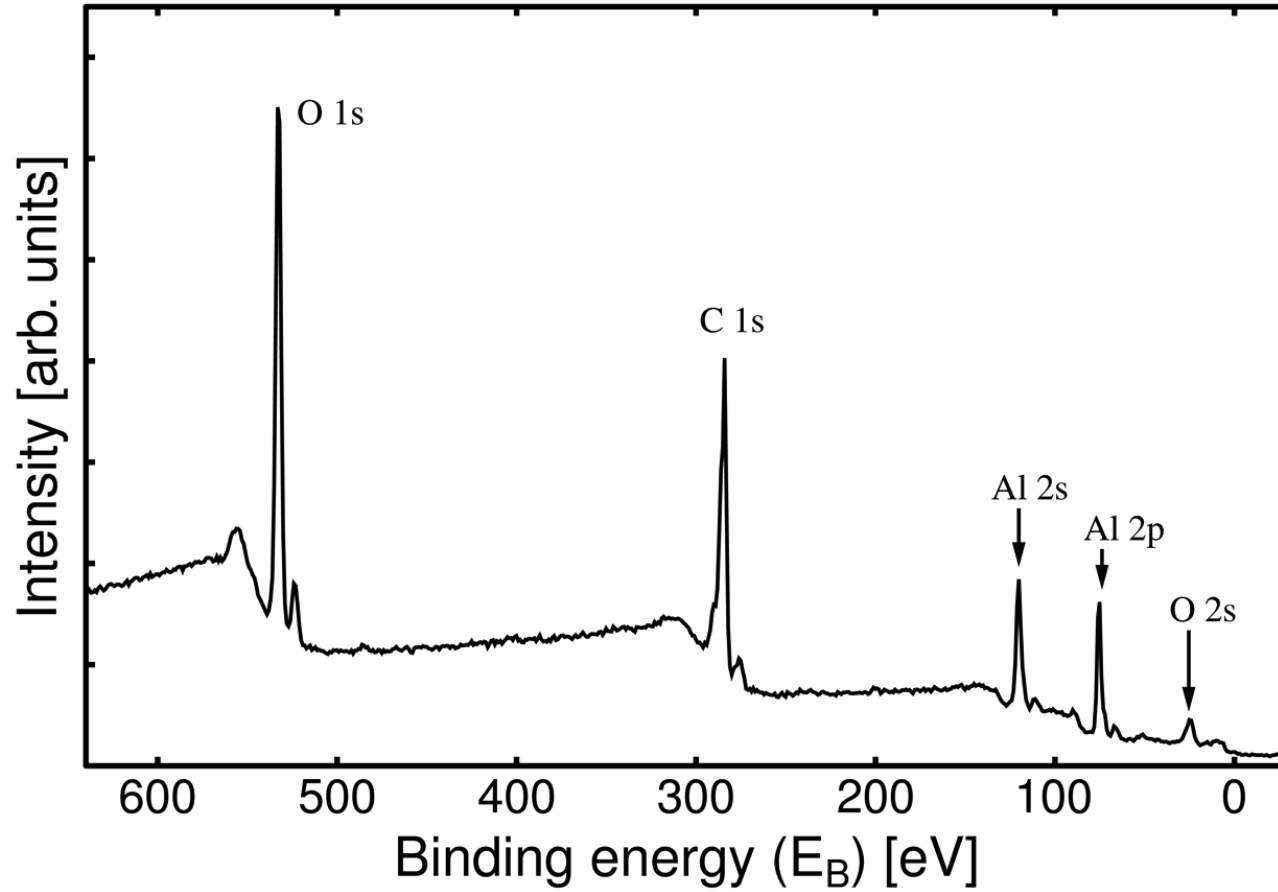
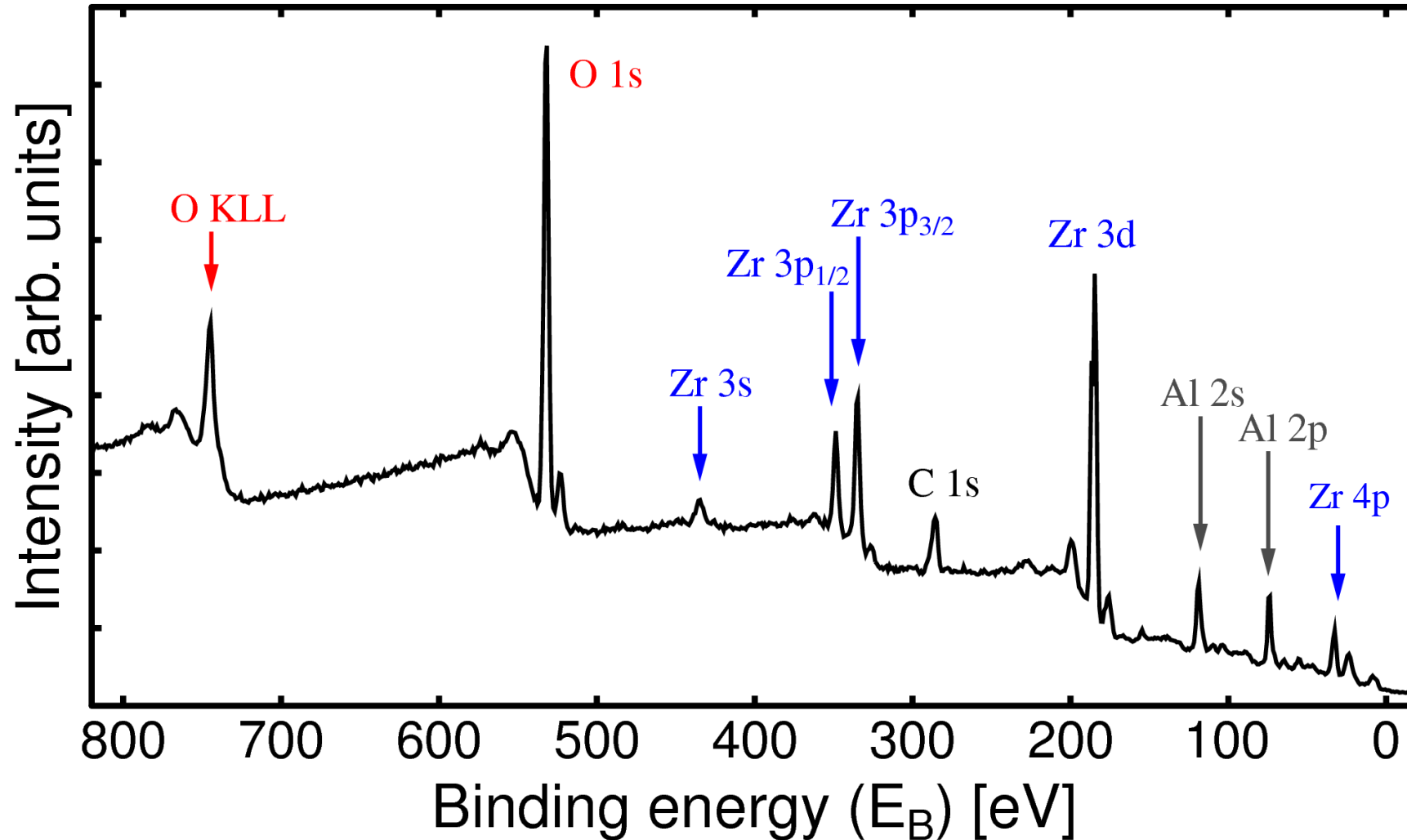


Table 3. Line Positions from Mg X-rays, in eV

17 Hf 4f ₇ (2)	102 Si 2p ₃ (1)	206 Nb 3d ₅ (3)	359 Lu 4p ₃ (53)
23 O 2s	105 Ga 3p ₃ (3)	208 Kr 3p ₃ (8)	359 Hg 4d ₅ (20)
25 Ta 4f ₇ (2)	108 Ce 4d ₅ (4)	213 Hf 4d ₅ (11)	362 Gd (A)
30 F 2s	110 Rb 3d ₅ (1)	229 S 2s	364 Nb 3p ₃ (15)
31 Ge 3d ₅ (1)	113 Be 1s	229 Ta 4d ₅ (12)	368 Ag 3d ₅ (6)
34 W 4f ₇ (2)	113 Ge (A)	230 Mo 3d ₅ (3)	378 K 2s
40 V 3p	114 Pr 4d	238 Rb 3p ₃ (9)	380 U 4f ₇ (11)
41 Ne 2s	118 Tl 4f ₇ (4)	241 Ar 2p ₃ (2)	385 Tl 4d ₅ (21)
43 Re 4f ₇ (2)	119 Al 2s	245 W 4d ₅ (12)	396 Mo 3p ₃ (17)
44 As 3d ₅ (1)	120 Nd 4d	263 Re 4d ₅ (14)	402 N 1s
45 Cr 3p ₃ (1)	124 Ge 3p ₃ (4)	264 Na (A)	402 Eu (A)
48 Mn 3p ₃ (1)	132 Sm 4d	265 Zn (A)	402 Sc 2p ₃ (5)
50 I 4d ₅ (2)	133 P 2p ₃ (1)	269 Sr 3p ₃ (11)	405 Cd 3d ₅ (7)
51 Mg 2p	133 Sr 3d ₅ (2)	270 Cl 2s	410 Ni (A)
52 Os 4f ₇ (3)	136 Eu 4d	279 Os 4d ₅ (15)	413 Pb 4d ₅ (22)
55 Fe 3p ₃ (1)	138 Pb 4f ₇ (5)	282 Ru 3d ₅ (4)	435 Ne (A)
56 Li 1s	143 As 3p ₃ (5)	284 Tb 4p ₃ (33)	439 Ca 2s
57 Se 3d ₅ (1)	150 Tb 4d	287 C 1s	440 Sm (A)
61 Co 3p ₃ (2)	153 Si 2s	293 Dy 4p ₃ (36)	443 Bi 4d ₅ (24)
62 Ir 4f ₇ (3)	154 Dy 4d	295 K 2p ₃ (3)	445 In 3d ₅ (8)
63 Xe 4d ₅ (2)	158 Y 3d ₅ (2)	297 Ir 4d ₅ (16)	458 Ti 2p ₃ (6)
64 Na 2s	159 Bi 4f ₇ (5)	301 Y 3p ₃ (12)	463 Ru 3p ₃ (22)
67 Ni 3p ₃ (2)	161 Ho 4d	306 Ho 4p ₃ (39)	483 Co (A)
69 Br 3d ₅ (1)	163 Se 3p ₃ (6)	309 Rh 3d ₅ (5)	486 Sn 3d ₅ (8)
73 Pt 4f ₇ (3)	165 S 2p ₃ (1)	316 Pt 4d ₅ (17)	498 Rh 3p ₃ (24)
74 Al 2p	169 Er 4d	319 Ar 2s	501 Sc 2s
75 Cs 4d	180 Tm 4d	320 Er 4p ₃ (42)	515 V 2p ₃ (8)
77 Cu 3p ₃ (2)	181 Zr 3d ₅ (2)	331 Zr 3p ₃ (14)	519 Nd (A)
85 Au 4f ₇ (4)	182 Br 3p ₃ (7)	333 Tm 4p ₃ (45)	530 Sb 3d ₅ (9)
87 Zn 3p ₃ (3)	185 Yb 4d ₅ (9)	335 Th 4f ₇ (9)	531 O 1s
88 Kr 3d ₅ (1)	189 Ga (A)	336 Au 4d ₅ (18)	534 Pd 3p ₃ (27)
90 Ba 4d ₅ (2)	191 B 1s	337 Pd 3d ₅ (5)	553 Fe (A)
90 Mg 2s	191 P 2s	337 Cu (A)	555 Pr (A)
100 Hg 4f ₇ (4)	197 Lu 4d ₅ (10)	342 Yb 4p ₃ (50)	565 Ti 2s
101 La 4d ₅ (3)	199 Cl 2p ₃ (2)	347 Ca 2p ₃ (3)	573 Ag 3p ₃ (31)

An A in parentheses denotes Auger line. Numbers in parentheses are spin doublet separations in electron volts. The photoelectron lines per element are included in the table. For brevity, 2p₃ equals 2p_{3/2}, 3d₅ equals 3d_{5/2}, etc.

Example 2



XPS

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Quantification

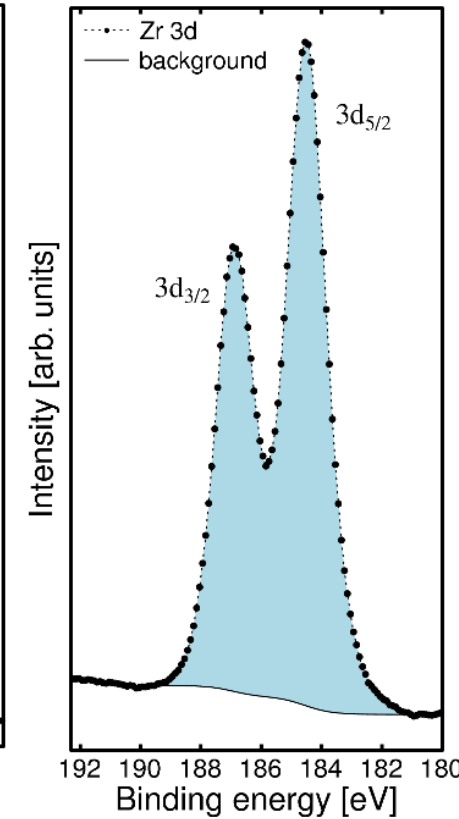
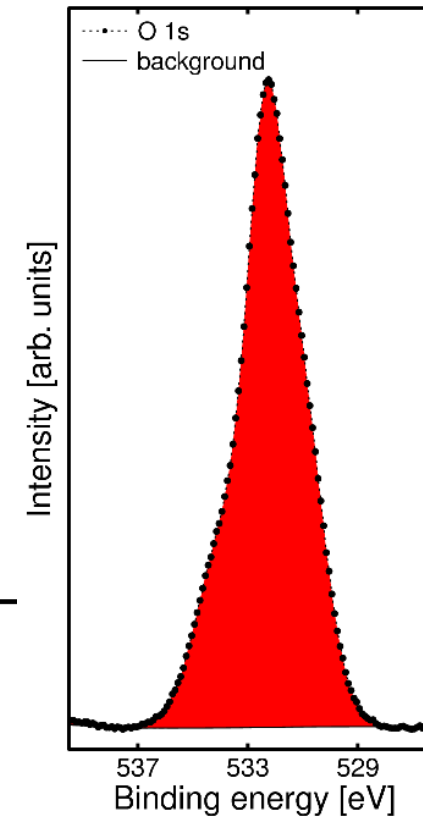
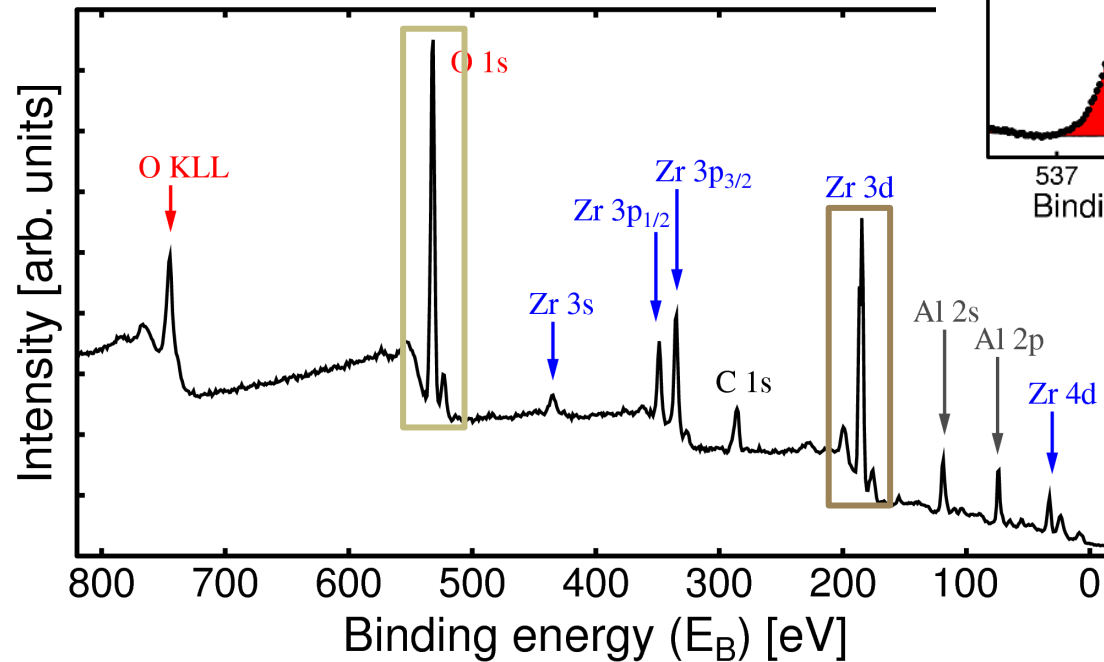
- Peak intensity proportional to surface concentration:

$$I_i \propto N_i a_i$$

- I_i = peak intensity
- N_i = atomic concentration
- a_i = atomic sensitivity factor
- Stoichiometry can be calculated using intensities and sensitivity factors
- Peak areas are best measure of intensity

For multi-element surface layer:

$$N_A = \frac{I_A / a_A}{\sum_i I_i / a_i}$$



Stoichiometry:

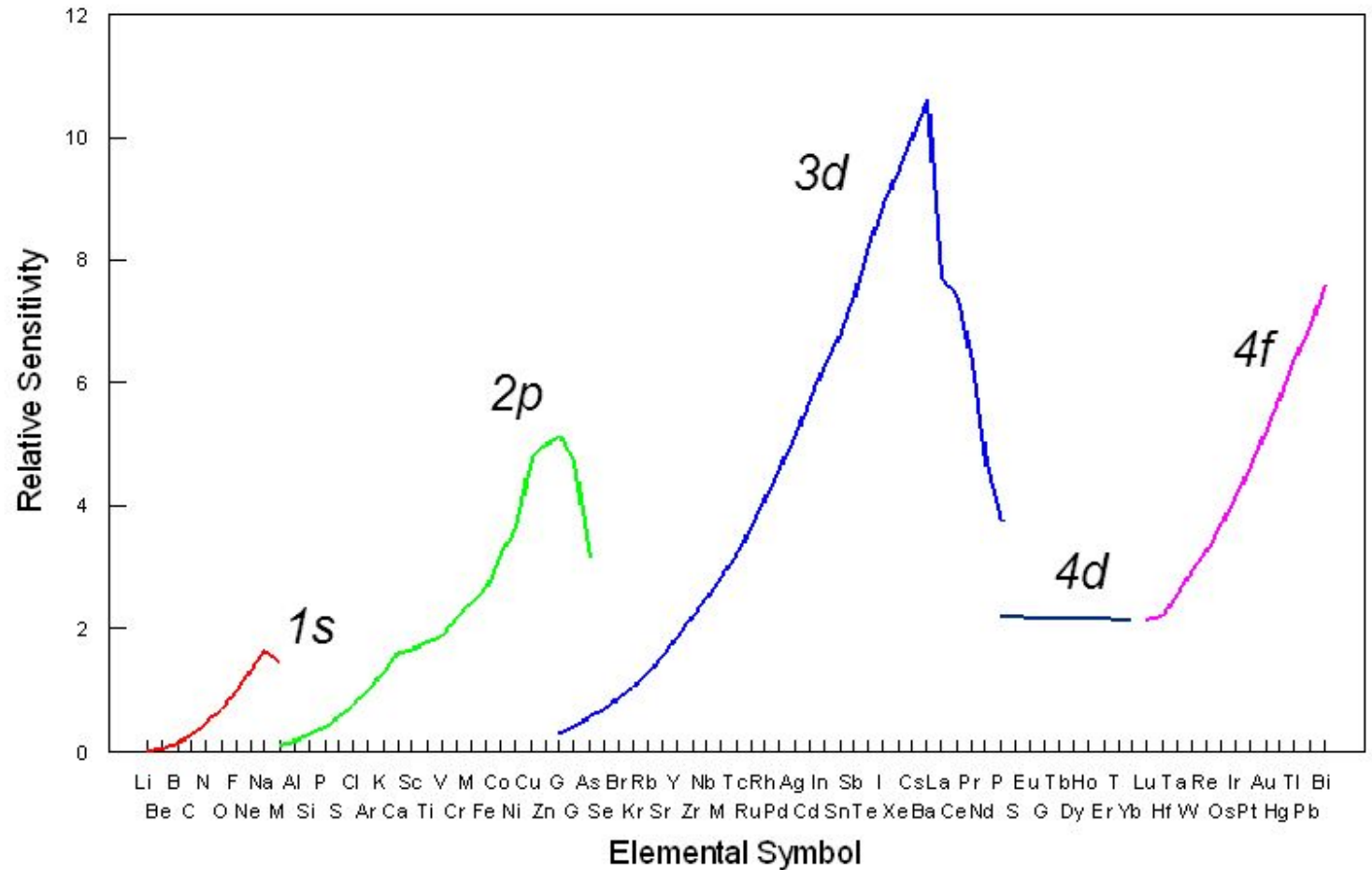
Zr: 12.56 %
 Al: 28.10 %
 O: 41.46 %
 C: 17.77 %

Atomic sensitivity factors (ASF)

- Sensitivity will vary greatly for different elements
- Combination of several factors:

$$a_i = \sigma_i \lambda_i$$

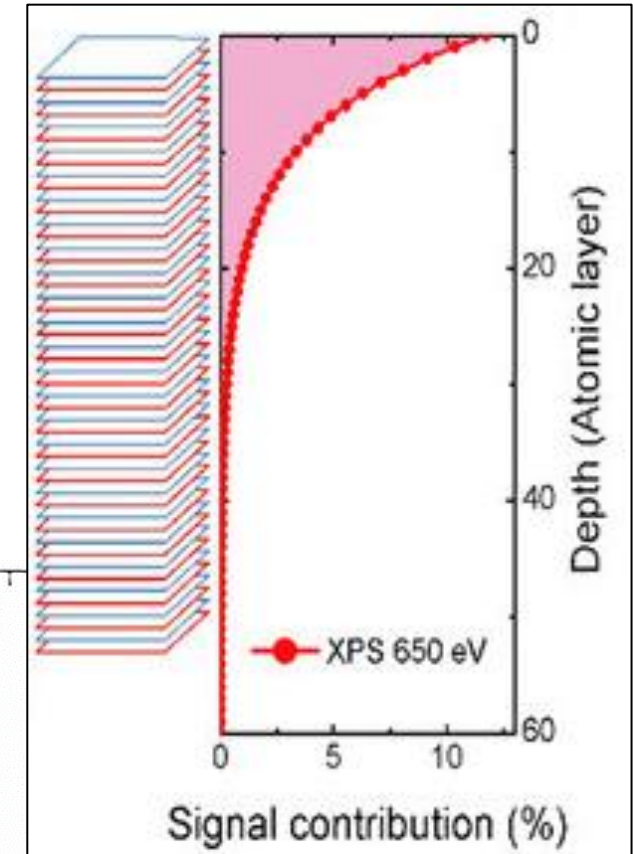
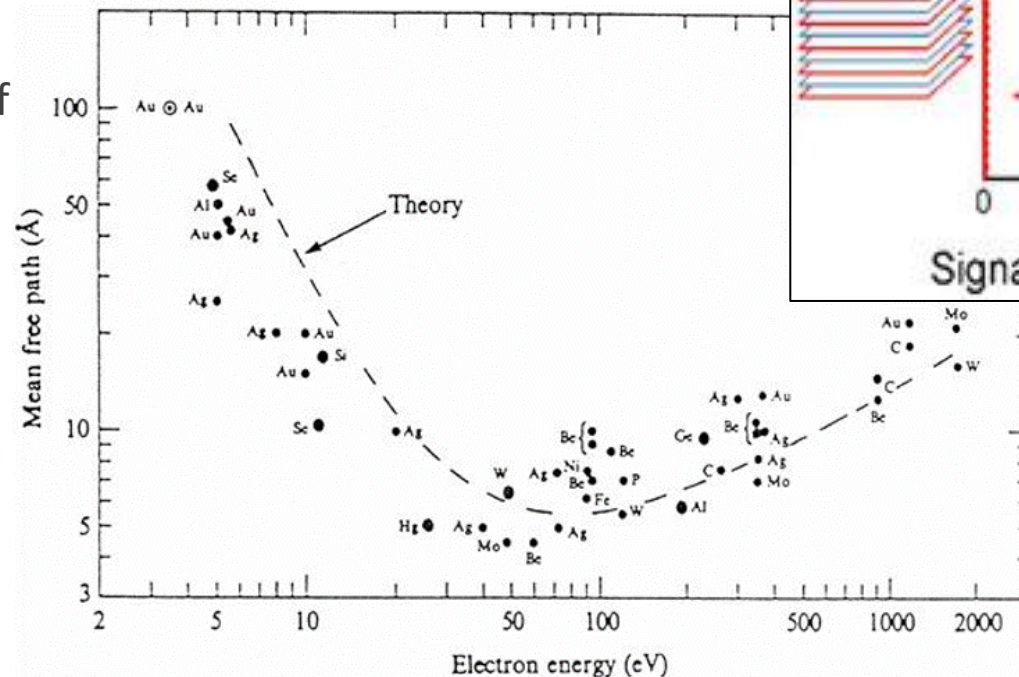
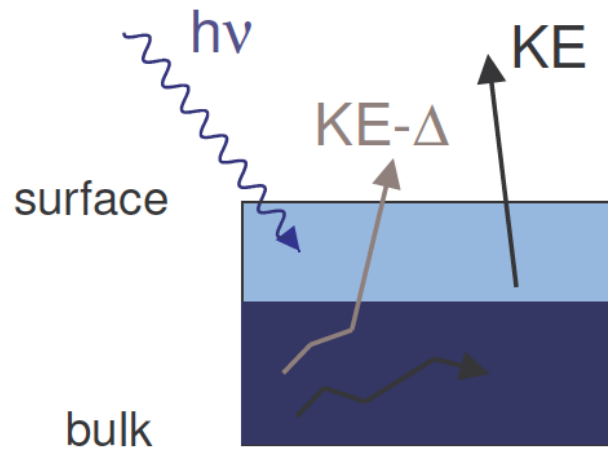
- σ_i – Scofield cross-section
 - Probability of X-ray producing photoelectron
- λ_i – Inelastic mean free path
 - Probability that the photoelectron will make it to the surface



Inelastic mean free path – λ

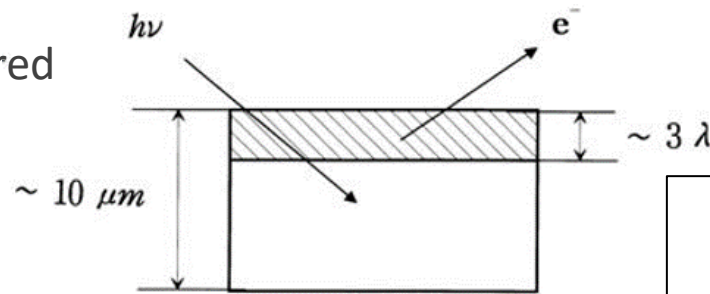
- Core level peaks only account for a small part of all photoelectrons reaching the analyzer
 - Number of electrons** (intensity) reaching surface with core level energy **decreases exponentially** with depth of photoionization
- Slight dependence on electron energy and elements in surface
- Most important reason for surface sensitivity of XPS analysis

$$I = I_0 e^{-\frac{d}{\lambda}}$$



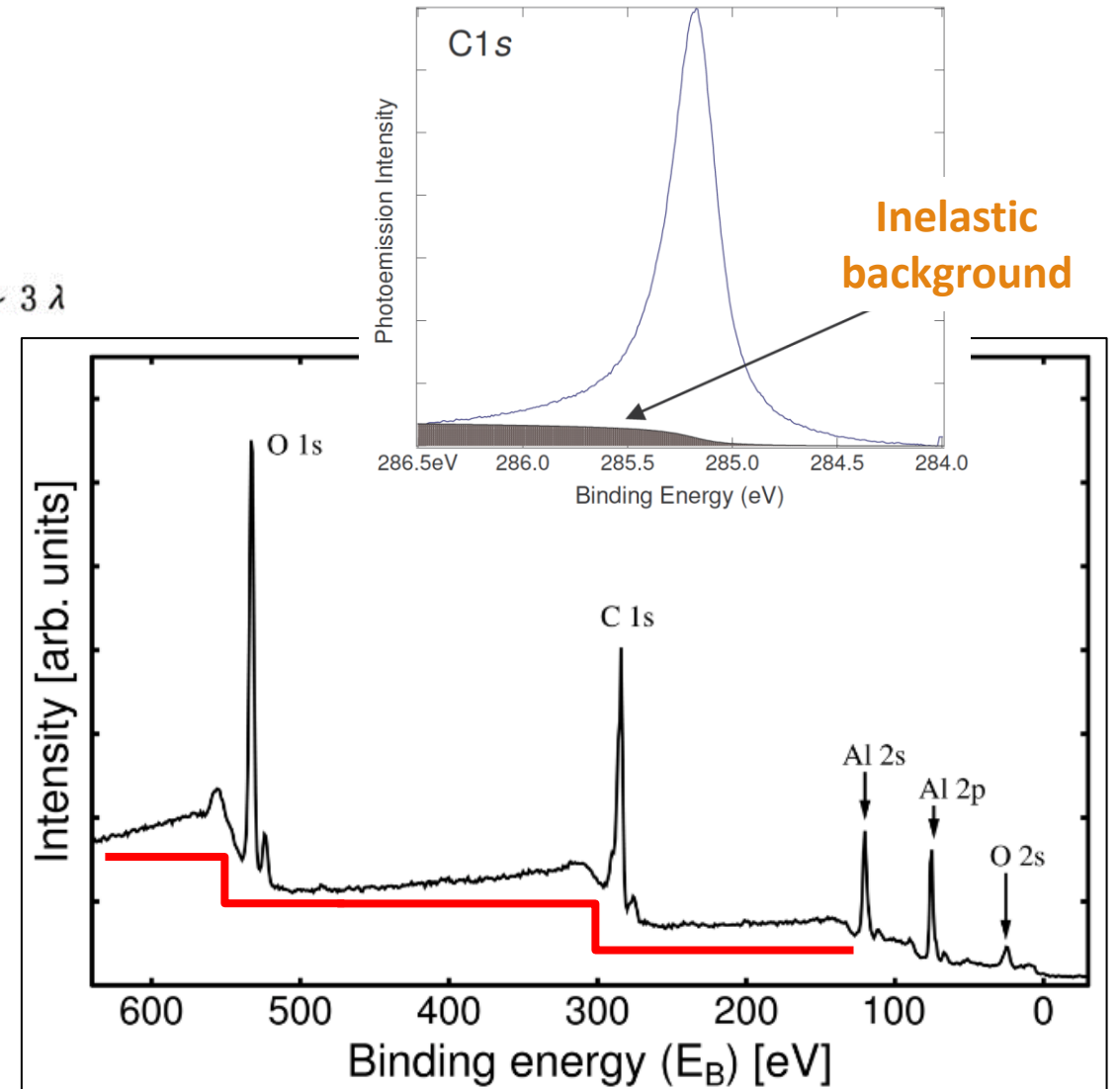
Inelastic background

- 63 % of all electrons scattered within one λ
- 95 % scattered in 3λ – **sampling depth**



Loss processes:

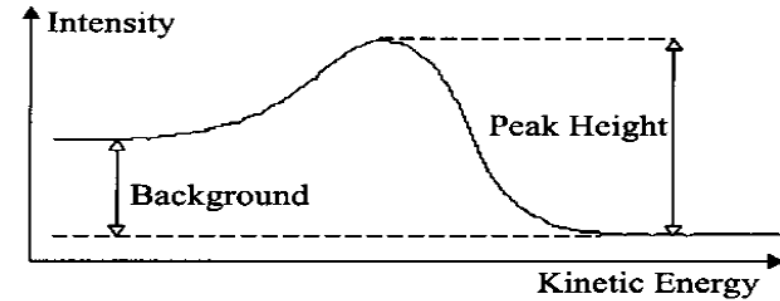
- Phonons: collective excitations of atoms (10 meV – 10 eV)
- Plasmons: collective excitations of electrons (5 eV – 20 eV)
- One electron excitations (50 eV –)
- Scattering losses result in a large increase in photoelectron intensity directly after each core level peak



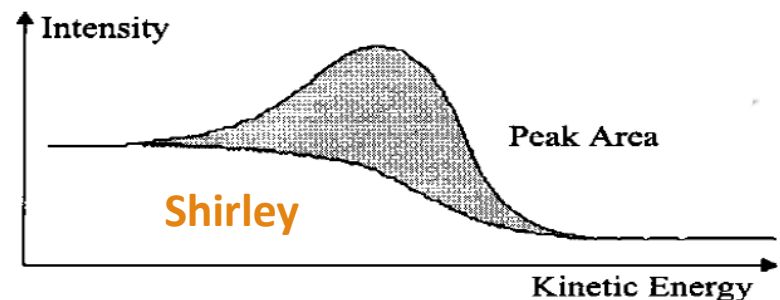
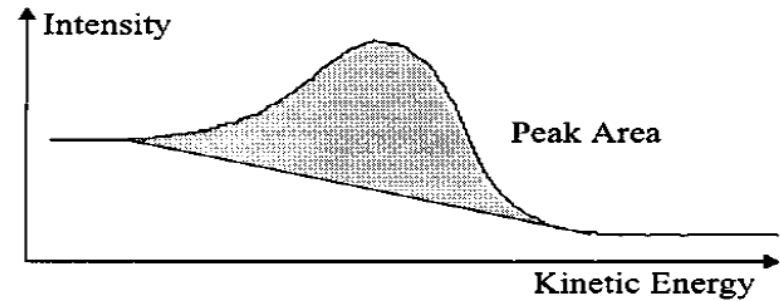
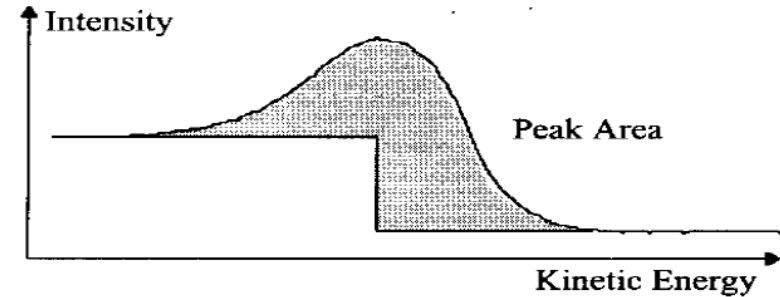
Background removal

How is peak intensity measured?

- Peak heights can sometimes be used
 - Result not very good – shapes not always the same
 - **Area** is almost always used
 - But background is not constant (nor linear) near peak
 - **Shirley** background is most commonly used
-
- With ASF's: accuracy better than 15 %
 - With standard samples on same instrument: ~5 %
 - Reproducibility (precision) better than 2 %



Worst

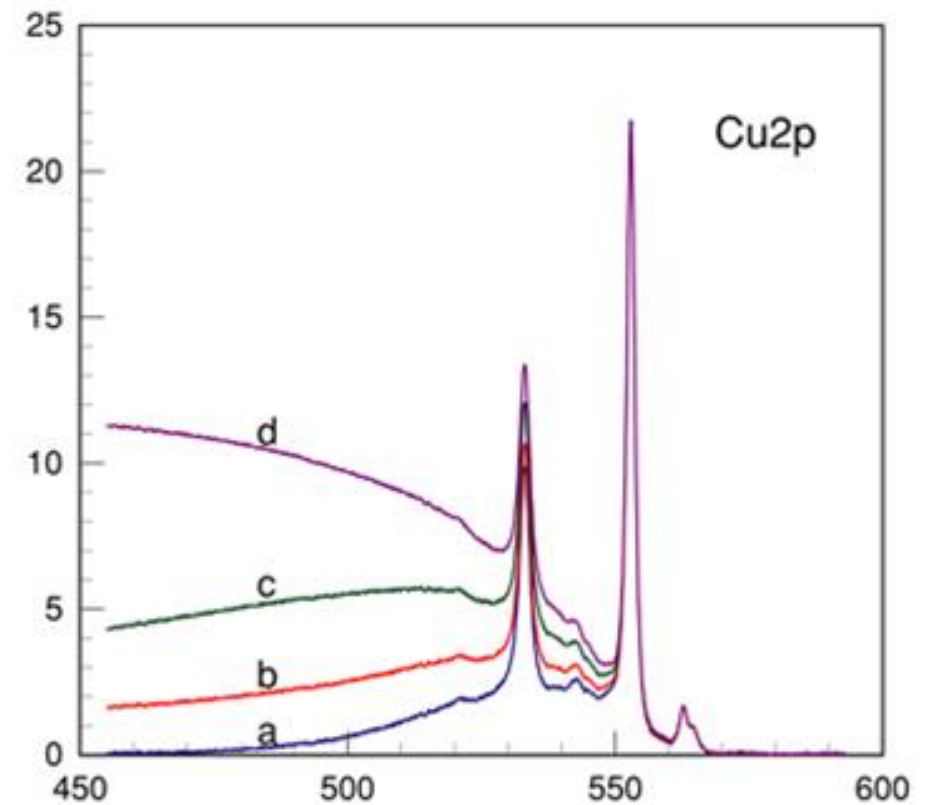
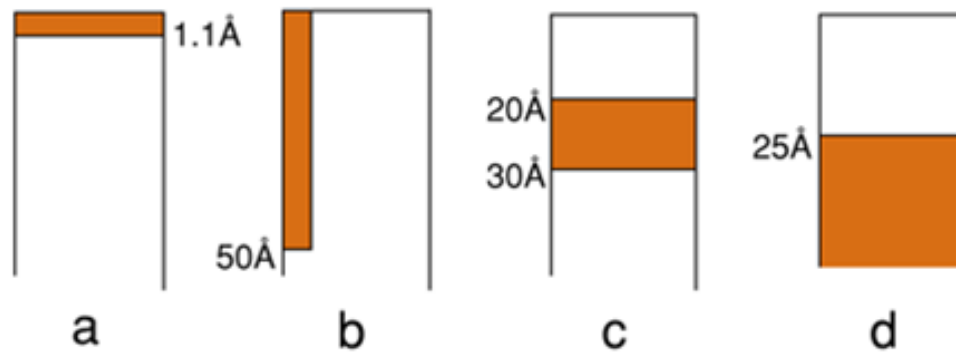


Best

Surface morphologies

Traditional XPS quantification assumes:

- Outer surface of sample is homogeneous
- Outer surface concentration is directly proportional to the main peak intensity
- Depending on the depth and lateral distribution of emitting atoms the **background can change dramatically**



XPS

X-Ray Photoelectron Spectroscopy

OUTLINE:

1. Background
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 2. Peak identification
3. Analysis and results
 1. Quantitative analysis & effects of sample
 2. Chemical environment & peak fitting
4. Technical issues & Auxiliary features
 1. Surface contamination & charging
 2. Ion beam sputtering & depth profiling
 3. Angle resolved XPS
 4. Small area analysis and imaging

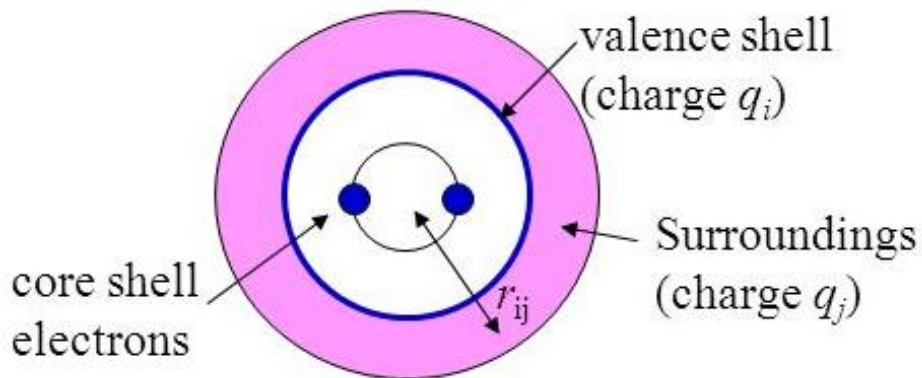
Chemical effect in XPS

Chemical shift:

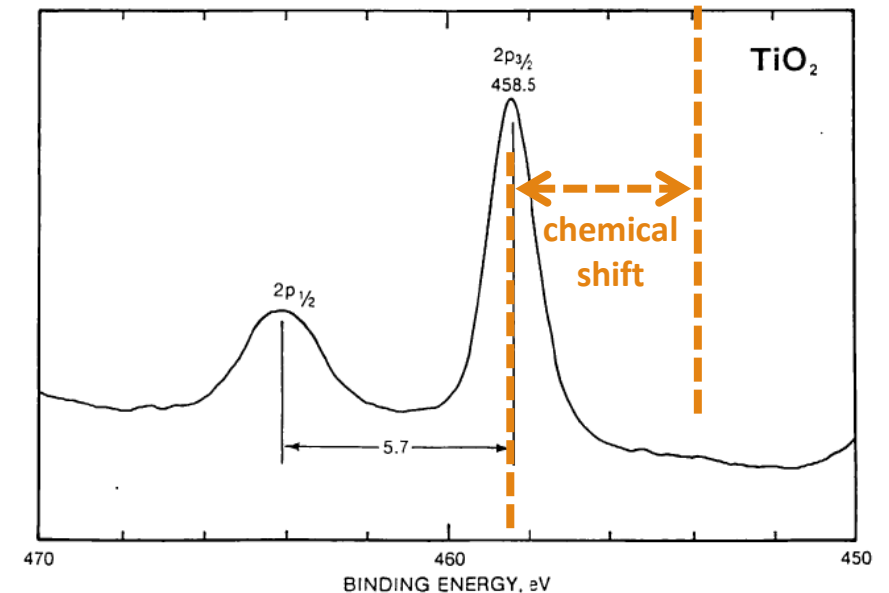
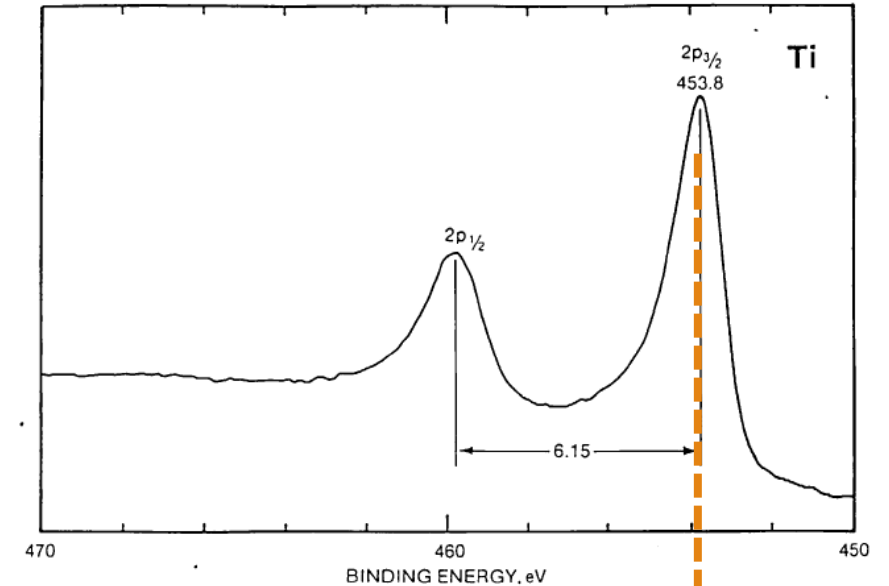
- Changes in the chemical bonding of an element will cause changes in the binding energy of core electrons

Core binding energies are determined by:

- Electrostatic interaction between electron and nucleus
- All other electrons (including valence) shield nuclear charge
- Removal or addition of electronic charge will alter this shielding



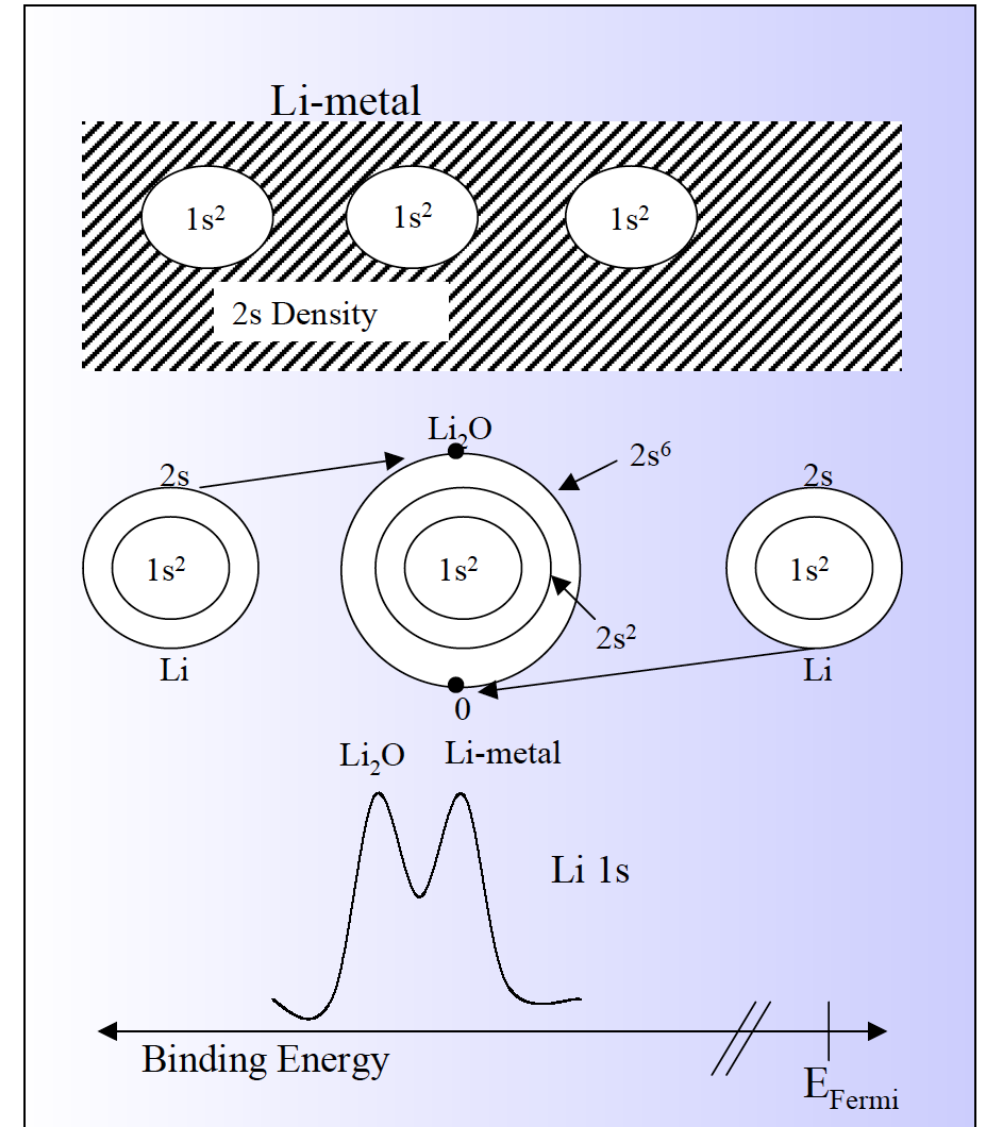
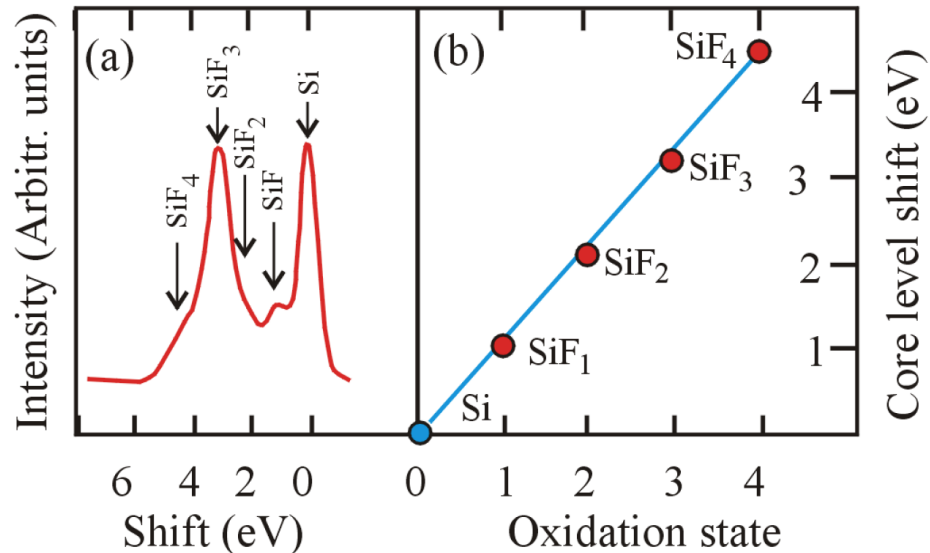
- Withdrawal of negative charge (oxidation) – increase in E_b
- Addition of negative charge – decrease in E_b



Chemical shift

Oxides compared to metals:

- Binding energy is lower in pure metals due to screening by conduction electrons
- Binding energy higher in metal oxides because electron density is lost to oxygen
- Ionic compounds: binding energy shift 1 eV / oxidation state!



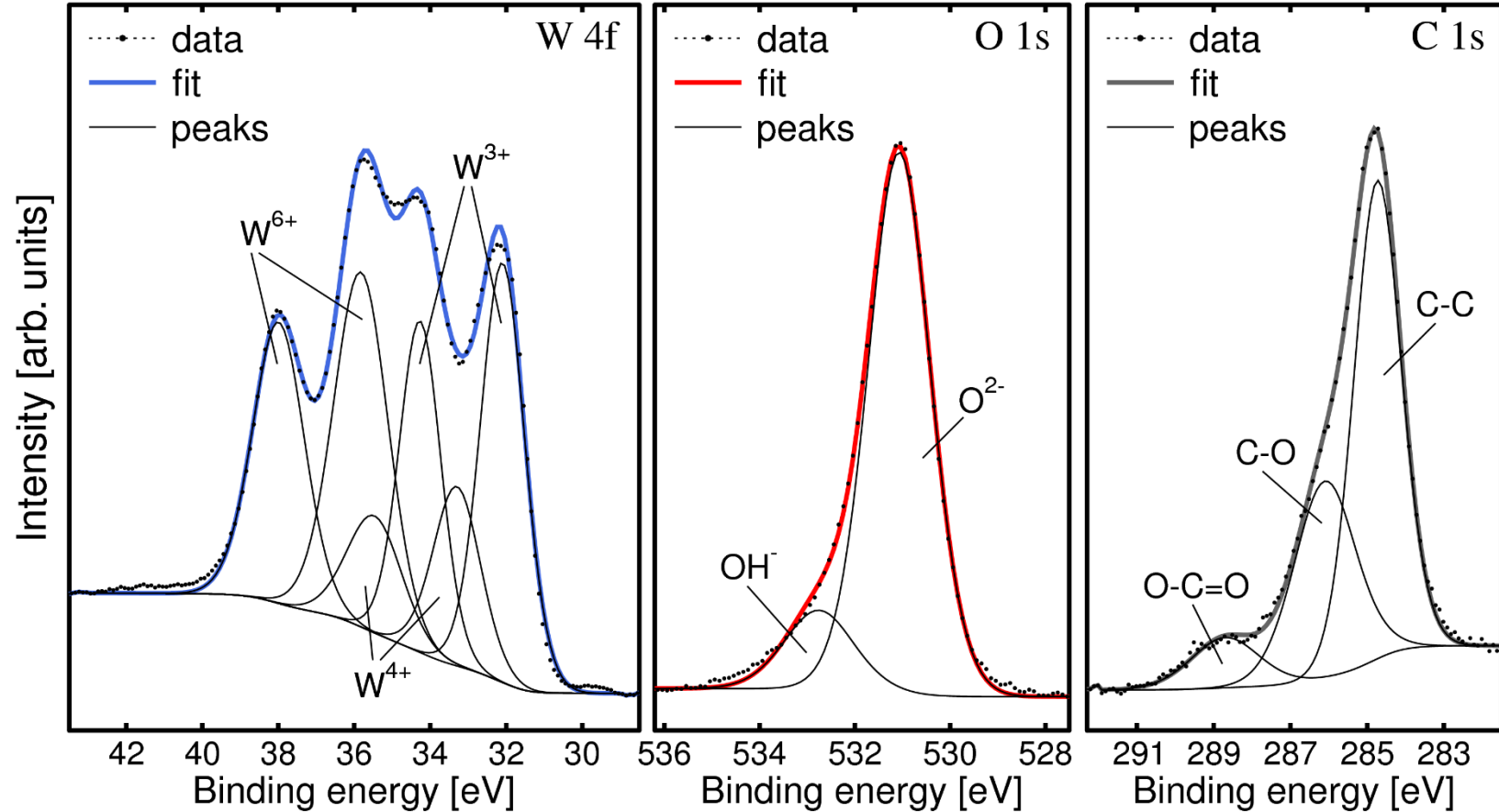
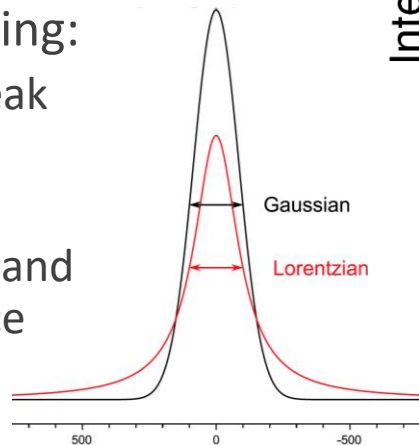
Peak fitting

Measured peaks usually contain signals from atoms in many different chemical environments

- Chemical species can be deconvoluted from spectra using peak fitting algorithms
- Gaussian (70 %) – Lorentzian (30 %) peak shapes (other GL ratios also common)

Useful in peak fitting:

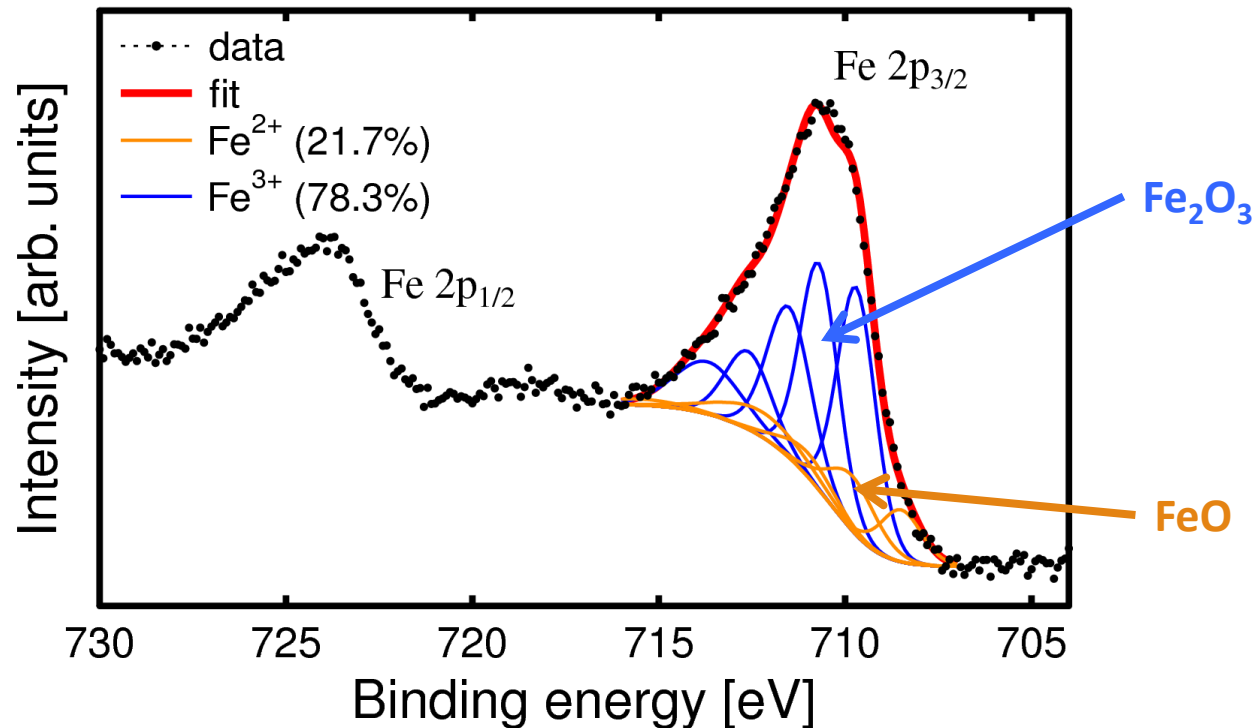
- Fixed ΔE_b and peak area ratios for doublets
- Known energies and FWHM (reference data)



Complex bonding

Complex bonding environments are typical for many materials

- A single compound will give an asymmetric peak shape
- Several GL peaks have to be fitted in order to get reproducibility



COMPOUND	2p _{3/2} BINDING ENERGY, eV	REF.
Fe	705	Φ
Fe ₂ B		MEC
FeB		MEC
FeS ₂		B4
Fe(C ₅ H ₅) ₂		CDH
Fe(C ₅ H ₅) ₂ I ₃		CDH
Zn ₂ Fe(CN) ₆		CSC
K ₄ Fe(CN) ₆		CSC
K ₄ Fe(CN) ₆		V
Na ₃ Fe(CN) ₅ N ₂		YN2
Na ₂ Fe(CN) ₅ NO		YN2
K ₃ Fe(CN) ₆		V
Fe ₂ P ₂ S ₆		B4
KFeS ₂		B4
FeS		CSC
Fe(CO) ₅		BC1
Fe(CO) ₂ (NO) ₂		BC1
Fe(C ₅ H ₅)(CO) ₃ BPh ₄		CDH
FeO		MZ
FeO		AC2
Fe ₂ O ₃		Φ
Fe ₂ O ₃		MZ
Fe ₂ O ₃		AC2
FeOOH		AC2
FeOOH		MZ
Fe ₃ O ₄		AC2
NaFeO ₂		AC2
NiFe ₂ O ₄		MZ
FeBr ₂		CSC
FeBr ₃		CSC
FeCl ₂		CSC
FeCl ₃		CSC
FeF ₂		CSC
FeF ₃		CSC
K ₃ FeF ₆		CSC

NIST database

National Institute of Standards and Technology

- srdata.nist.gov/xps/
- Large database with reference XPS data
- Very useful for determining chemical states
- Literature references for all given data

- [Introduction](#)
- [Search Menu](#)
- [Data Field](#)
- [Definitions](#)
- [Version History](#)
- [Disclaimer](#)
- [Acknowledgments](#)
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NIST X-ray Photoelectron Spectroscopy Database

NIST Standard Reference Database 20, Version 4.1

Data compiled and evaluated
by

Alexander V. Naumkin, Anna Kraut-Vass, Stephen W. Gaarenstroom, and Cedric J. Powell

Co	2p3/2	[N(C2H5)4]2CoBr4	780.10	Click
Co	2p3/2	[N(C2H5)4]2CoCl4	780.60	Click
Co	2p3/2	[N(C4H9)4]2[Co(NCC(S)C(S)CN)2]	780.00	Click
Co	2p3/2	[N(C4H9)4]2[Co(NCC(S)C(S)CN)2]	780.20	Click
Co	2p3/2	[N(CH3)4]2[CoSe(CN)4]	779.40	Click
Co	2p3/2	Al2CoO4	781.10	Click
Co	2p3/2	Al2CoO4	780.60	Click
Co	2p3/2	Al2CoO4	780.80	Click
Co	2p3/2	Co	778.30	Click
Co	2p3/2	Co	777.90	Click
Co	2p3/2	Co	778.32	Click
Co	2p3/2	Co	778.50	Click
Co	2p3/2	Co	778.10	Click
Co	2p3/2	Co	778.50	Click
Co	2p3/2	Co	778.20	Click
Co	2p3/2	Co	777.80	Click
Co	2p3/2	Co	778.00	Click
Co	2p3/2	Co	778.30	Click
Co	2p3/2	Co((C6H5)3PO)2(NO3)2	781.20	Click
Co	2p3/2	Co(NH3)6Cl3	781.10	Click
Co	2p3/2	Co(NH3)6Cl3	782.20	Click

Step 1. Choose type of data:

- Binding Energy
- Auger Kinetic Energy
- Auger Parameter
- Doublet Separation
- Surface/Interface Core-Level Shift
- Chemical Shift:

[Go to Step 2](#)

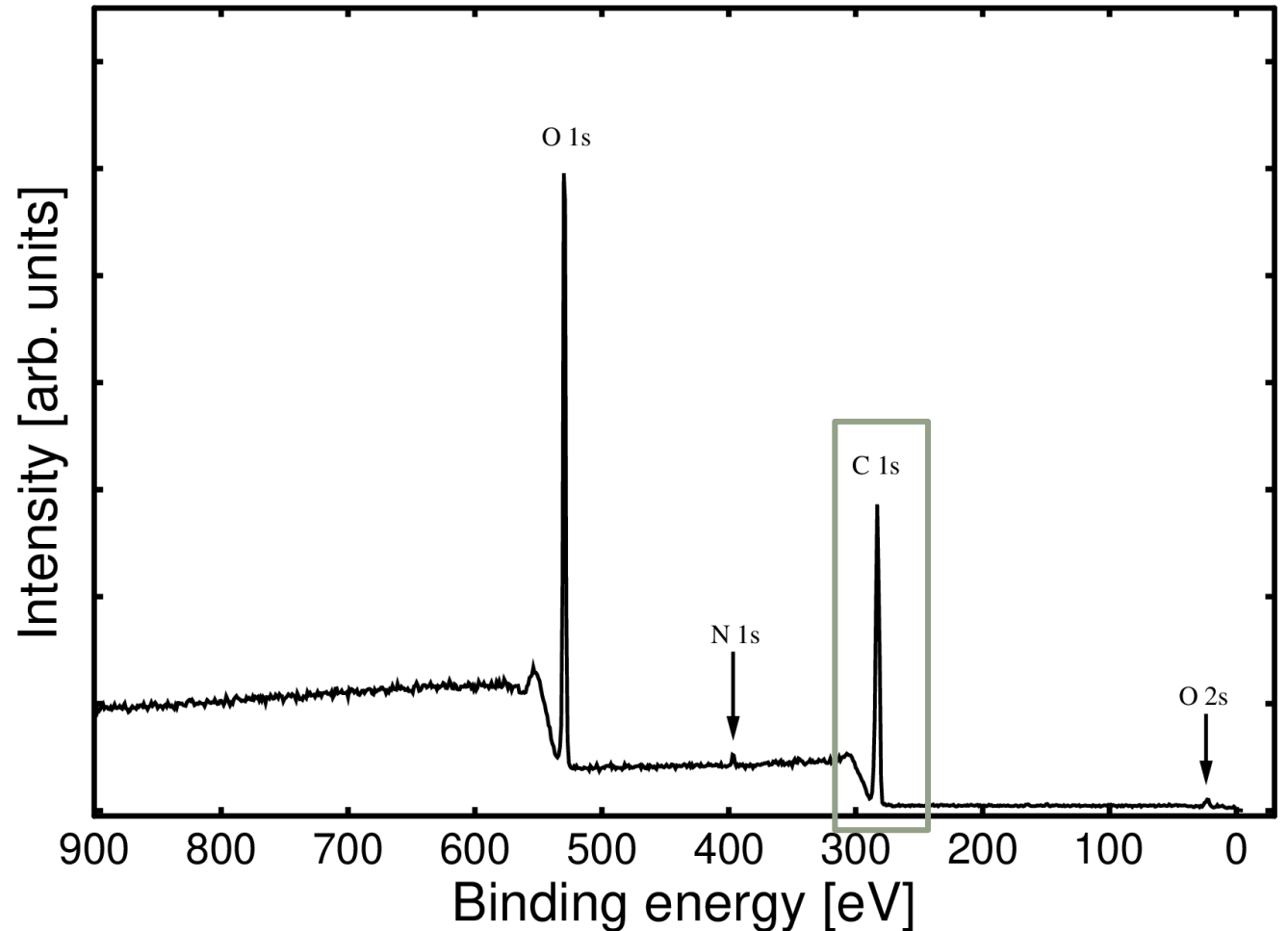
Step 2. Select an element for binding energy:

IA	IIA	IIIB	IVB	VB	VIB	VII B	VIII	IB	IIB	IIIA	IVA	VA	VIA	VIIA	VIIIA		
¹ H															² He		
³ Li	⁴ Be						Metals			⁵ B	⁶ C	⁷ N	⁸ O	⁹ F	¹⁰ Ne		
¹¹ Na	¹² Mg						Transition metals				¹³ Al	¹⁴ Si	¹⁵ P	¹⁶ S	¹⁷ Cl	¹⁸ Ar	
							Metalloids										
							Nonmetals										
¹⁹ K	²⁰ Ca	²¹ Sc	²² Ti	²³ V	²⁴ Cr	²⁵ Mn	²⁶ Fe	²⁷ Co	²⁸ Ni	²⁹ Cu	³⁰ Zn	³¹ Ga	³² Ge	³³ As	³⁴ Se	³⁵ Br	³⁶ Kr
³⁷ Rb	³⁸ Sr	³⁹ Y	⁴⁰ Zr	⁴¹ Nb	⁴² Mo	⁴³ Tc	⁴⁴ Ru	⁴⁵ Rh	⁴⁶ Pd	⁴⁷ Ag	⁴⁸ Cd	⁴⁹ In	⁵⁰ Sn	⁵¹ Sb	⁵² Te	⁵³ I	⁵⁴ Xe
⁵⁵ Cs	⁵⁶ Ba	⁵⁷ La	⁷² Hf	⁷³ Ta	⁷⁴ W	⁷⁵ Re	⁷⁶ Os	⁷⁷ Ir	⁷⁸ Pt	⁷⁹ Au	⁸⁰ Hg	⁸¹ Tl	⁸² Pb	⁸³ Bi	⁸⁴ Po	⁸⁵ At	⁸⁶ Rn
⁸⁷ Fr	⁸⁸ Ra	⁸⁹ Ac	¹⁰⁴ Rf	¹⁰⁵ Db	¹⁰⁶ Sg	¹⁰⁷ Bh	¹⁰⁸ Hs	¹⁰⁹ Mt									
lanthanides			⁵⁸ Ce	⁵⁹ Pr	⁶⁰ Nd	⁶¹ Pm	⁶² Sm	⁶³ Eu	⁶⁴ Gd	⁶⁵ Tb	⁶⁶ Dy	⁶⁷ Ho	⁶⁸ Er	⁶⁹ Tm	⁷⁰ Yb	⁷¹ Lu	
actinides			⁹⁰ Th	⁹¹ Pa	⁹² U	⁹³ Np	⁹⁴ Pu	⁹⁵ Am	⁹⁶ Cm	⁹⁷ Bk	⁹⁸ Cf	⁹⁹ Es	¹⁰⁰ Fm	¹⁰¹ Md	¹⁰² No	¹⁰³ Lr	

Practical example – Cellulose

Large area survey scan from cellulose:

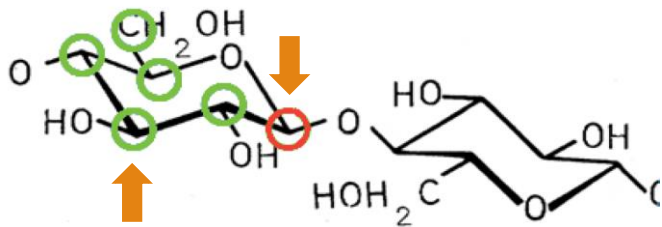
- Carbon and oxygen
- Elemental composition can be calculated
- O/C ratio measured
- Trace level impurities detected – nitrogen
- Zooming in on individual peaks will give you a lot more information!



Practical example – Cellulose

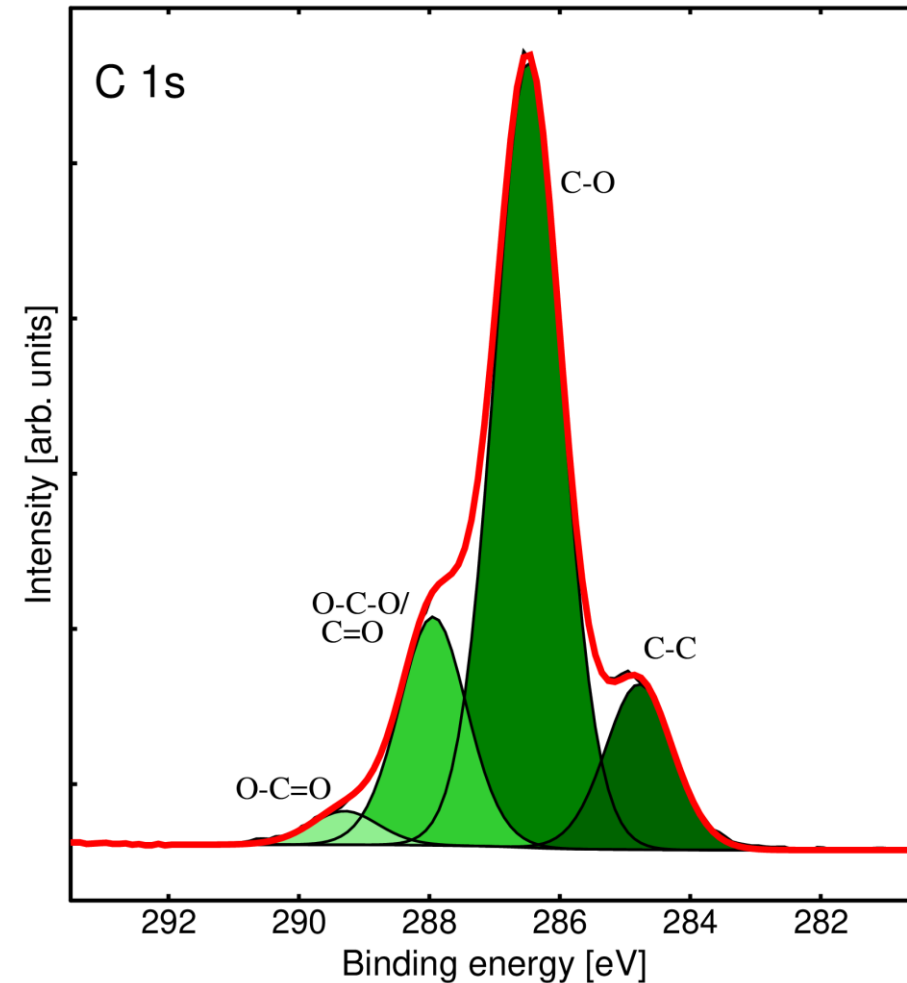
High resolution spectra:

- C 1s
- More components than a single Gaussian



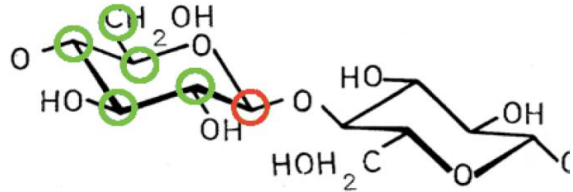
Understanding the material greatly improves the analysis

- Locating peaks
- Assigning peak energies



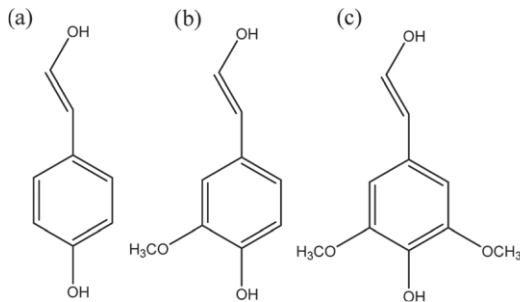
Cellulose vs lignin

Cellulose:



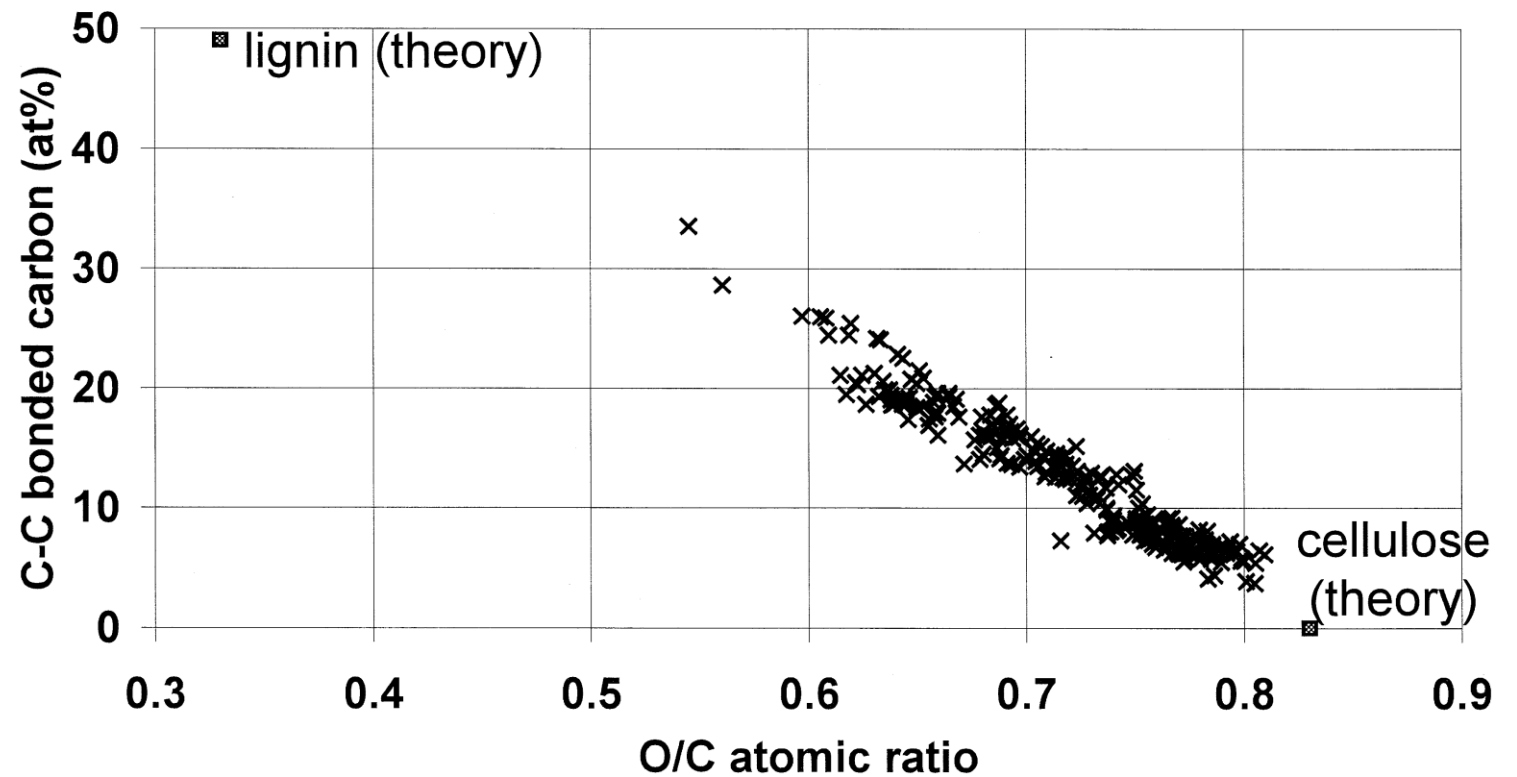
- O/C atomic ratio: 0.83
- C-C at.%: 0 %

Lignin (monolignols):



- O/C atomic ratio: 0.33
- C-C at.%: 49 %

O/C vs. C_1/C_{tot} for 254 measurements



[L.-S. Johansson, et al., *Appl. Surf. Sci.* 144-145 (1999) 92-95.]

XPS

X-Ray Photoelectron Spectroscopy

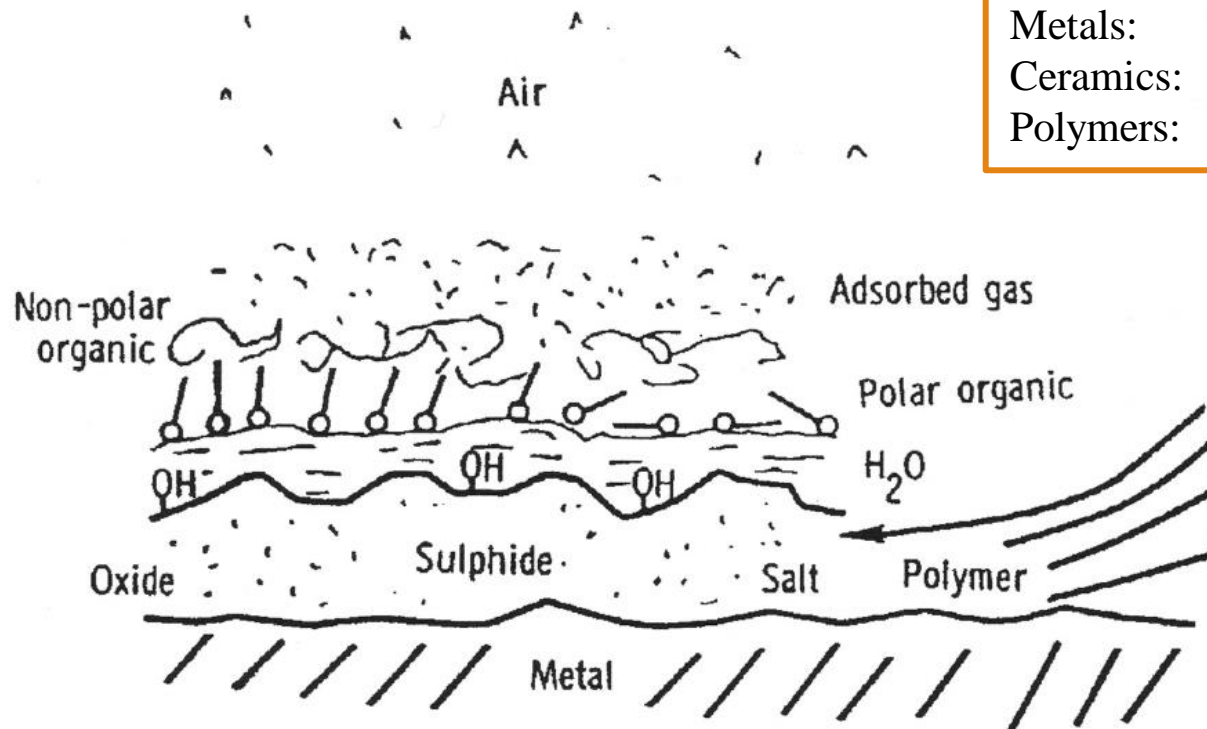
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1. Background
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Surface contamination

Ambient C (at.-%):

Metals:	40 – 60 %
Ceramics:	20 – 40 %
Polymers:	1 – 10 %



Surface contamination is always a big problem

- Oxidation
- Advantageous carbon

Carbon contamination

- Exists on all samples that have not been prepared in vacuum!

Sources:

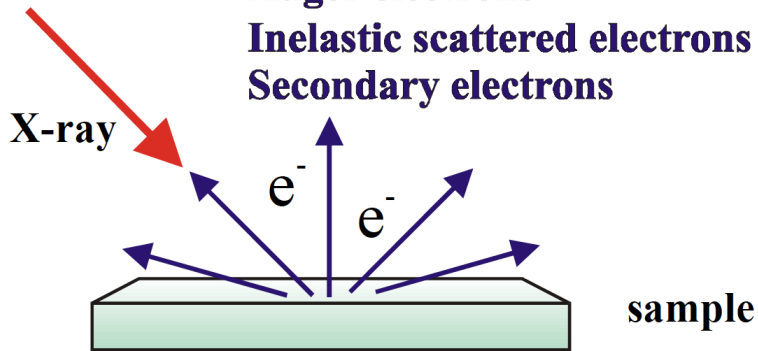
- Organic molecules in air
- *In situ*:
 - Contamination due to pumping oil
 - Desorption from other samples in chamber

Surface charging

Electrons are continuously removed from the surface of the sample:

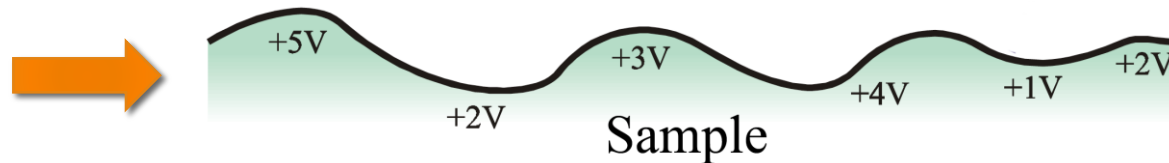
- Metals: electron loss is compensated
- Insulators: surface will collect (non-uniform) charge

Photoelectrons
Auger electrons
Inelastic scattered electrons
Secondary electrons



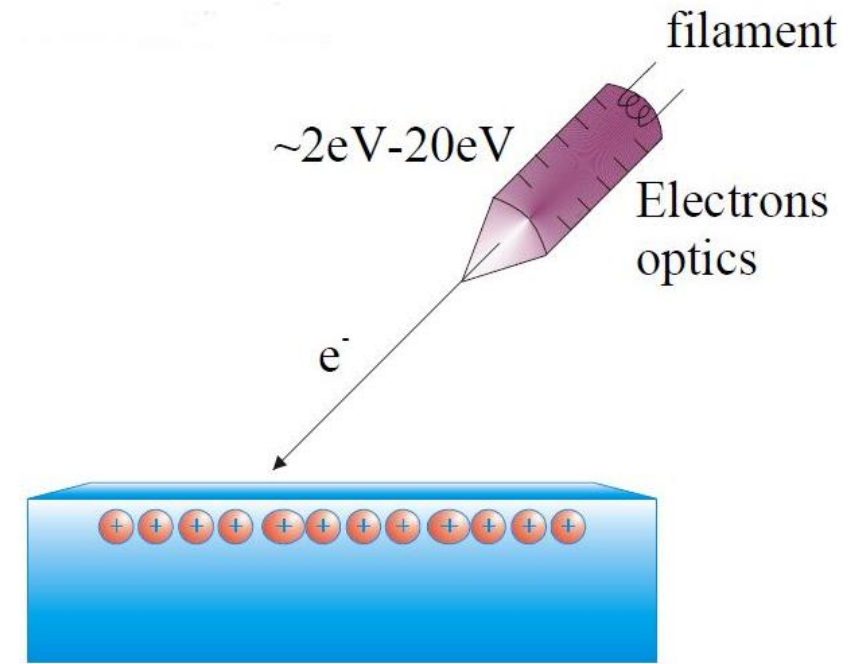
Non-uniform surface charging:

- Broadening of peaks
- Shift in peak energies



Low energy electron flood gun:

- Introduces excess electrons
- May affect surface bonding
- Not always reliable for maintaining a constant surface charge...



Energy calibration

Reference peaks can be used for calibration of peak positions on insulating samples

- All spectra can be shifted to align a certain peak with known binding energy

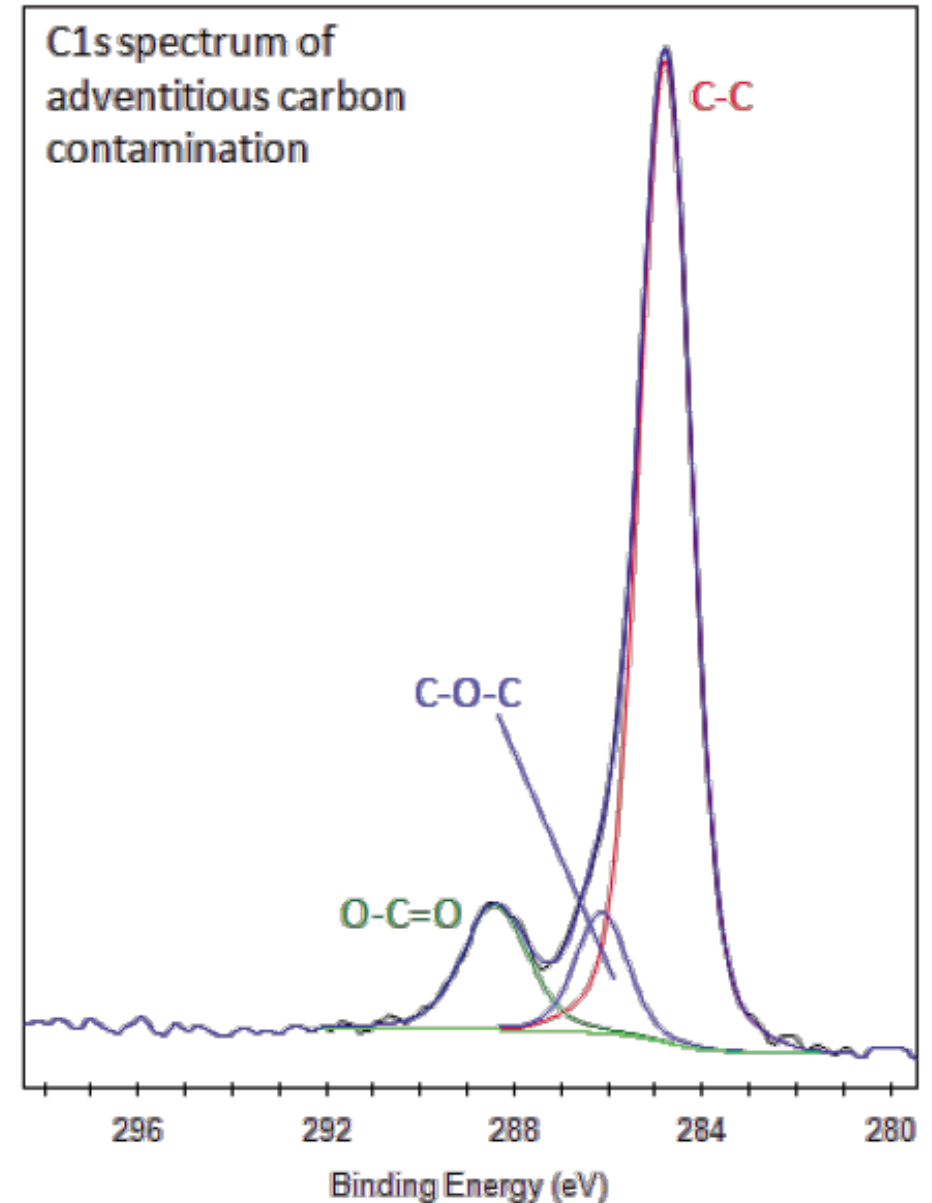
Adventitious carbon:

- C-C bonding in C 1s spectrum: 284.8 eV
- **NOTE:** Polymer scientist sometimes use 285.0 eV

Gold surface:

- Au 4f_{7/2}: 84.0 eV

Other peaks with known position in sample



Ion beam sputtering

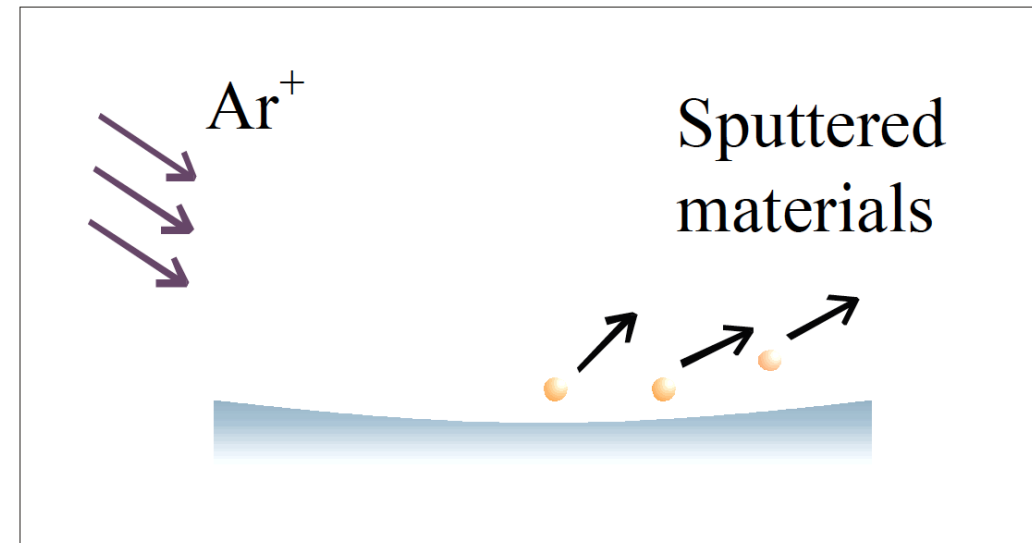
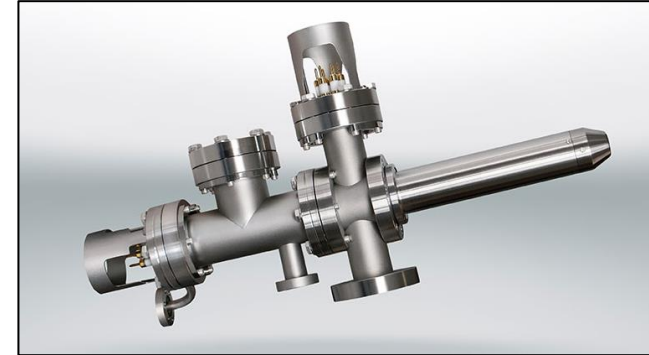
Ar-ion guns are often included in XPS-analysis chambers

- Ion energies usually 0-10 keV

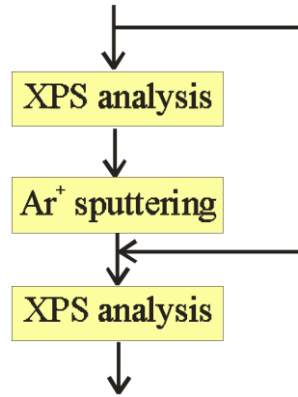
Removal of surface layers:

- Surface contamination
- Oxide removal
- Depth analysis

- NOTE: May affect surface chemistry and composition of materials
- Not always a good idea for XPS

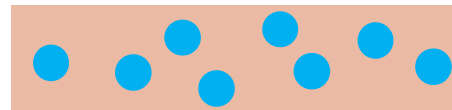


Depth profiling

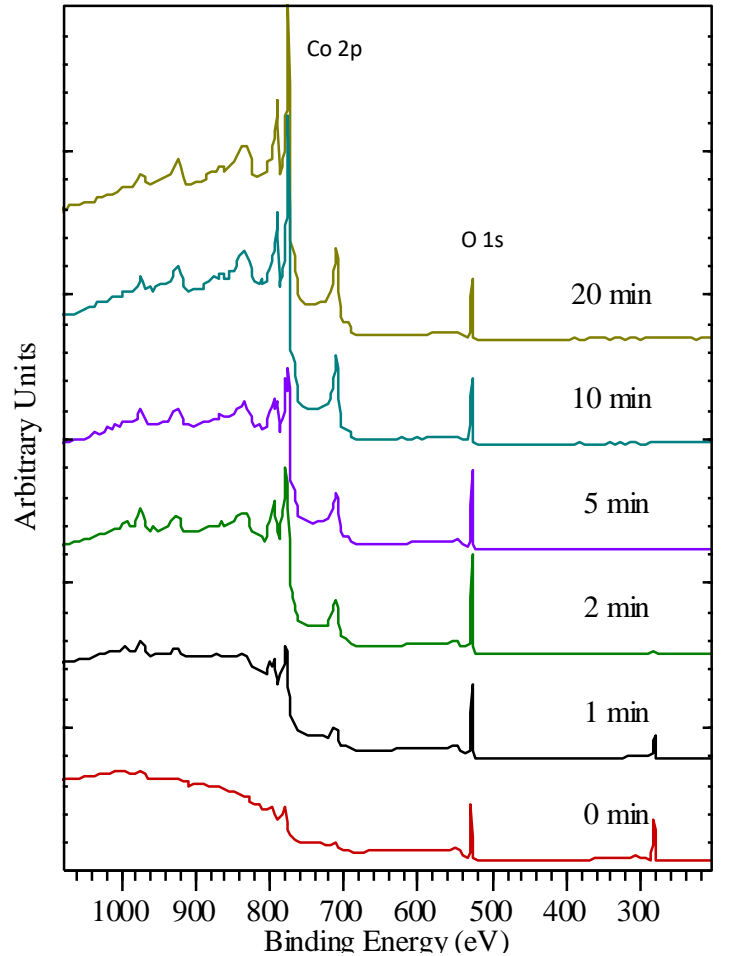
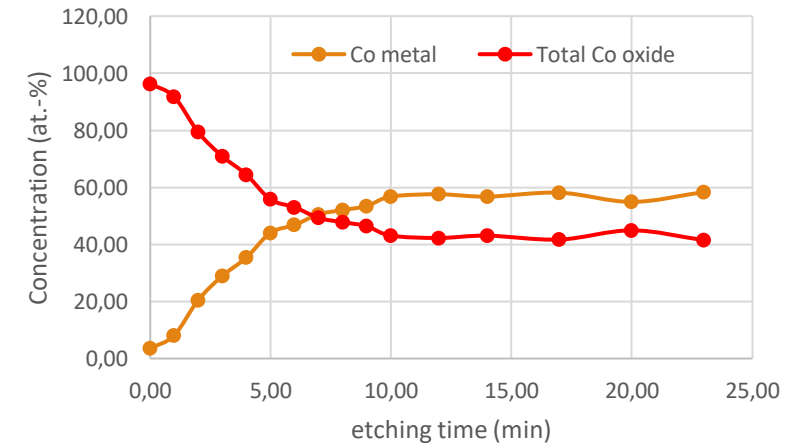
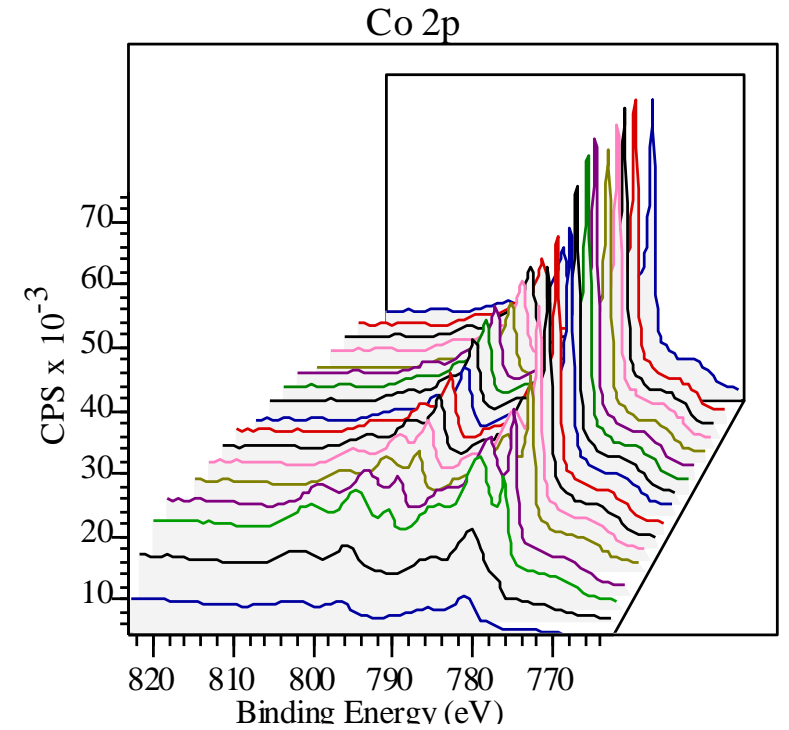
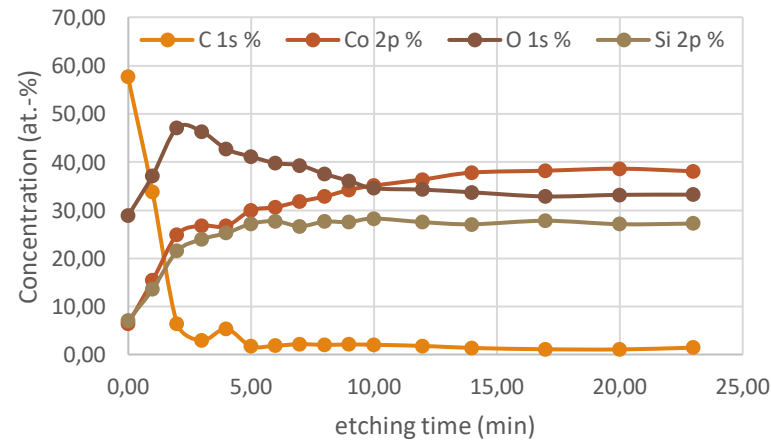


Example:

- SiO_x + embedded Co clusters



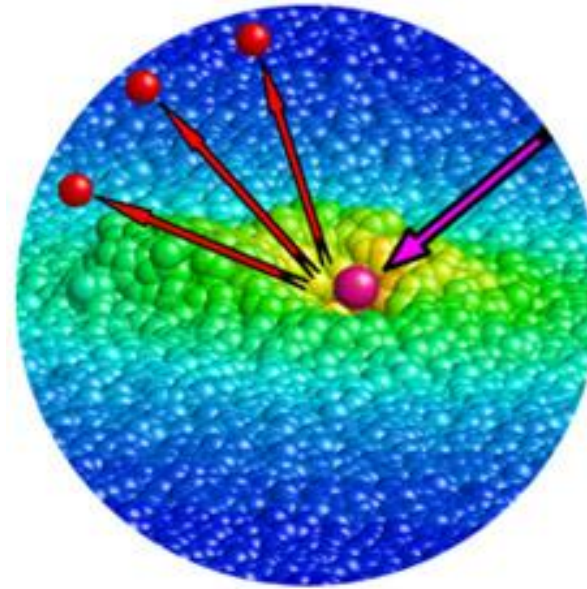
- Elemental depth profile
- Oxidation level vs depth!



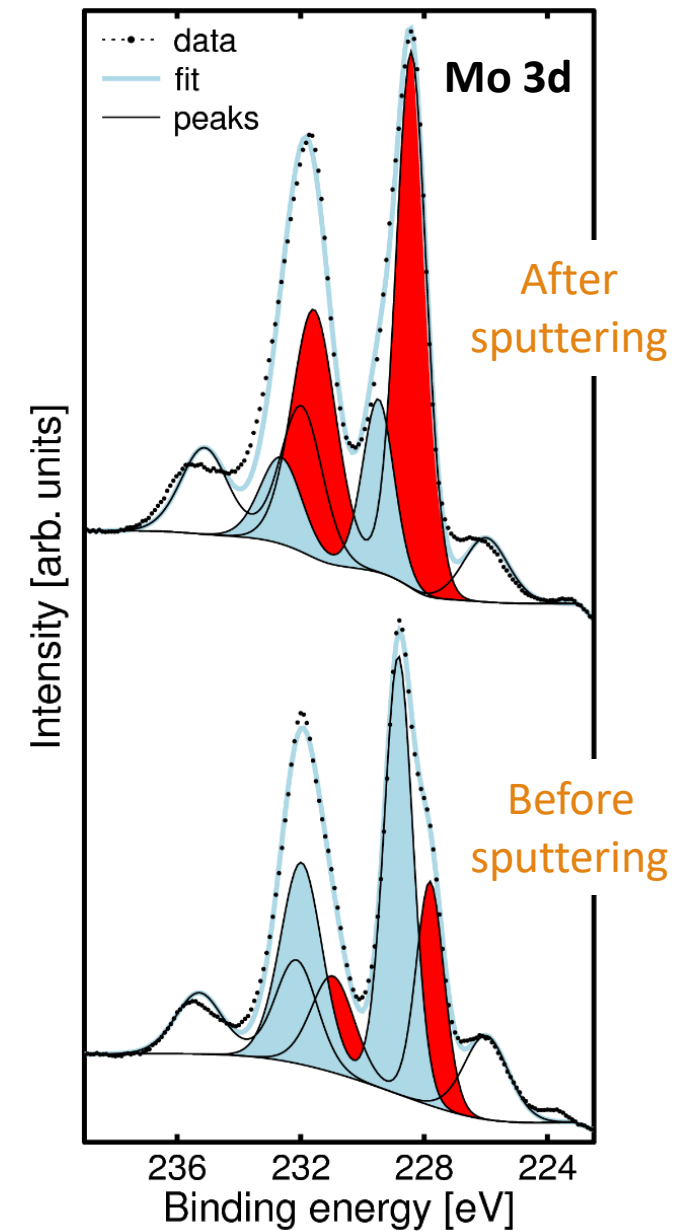
Radiation induced effects

Several factors affect accuracy and depth resolution when using ion beams:

- Non-uniform ion beam intensity/impurity ions
- Re-deposition of sputtered species
- Adsorption of residual gases
- Surface roughness (original and ion-induced)
- Crystalline structure and defects
- Preferential sputtering
- Atomic mixing in layered materials
- Ion implantation
- Decomposition of compounds



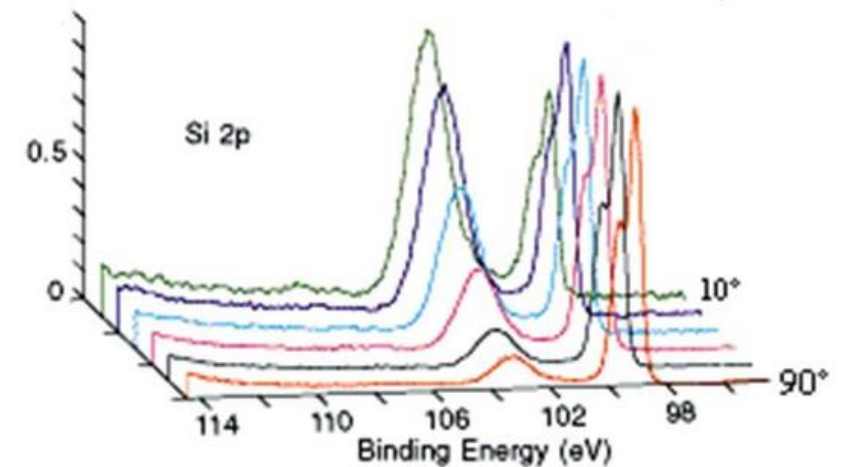
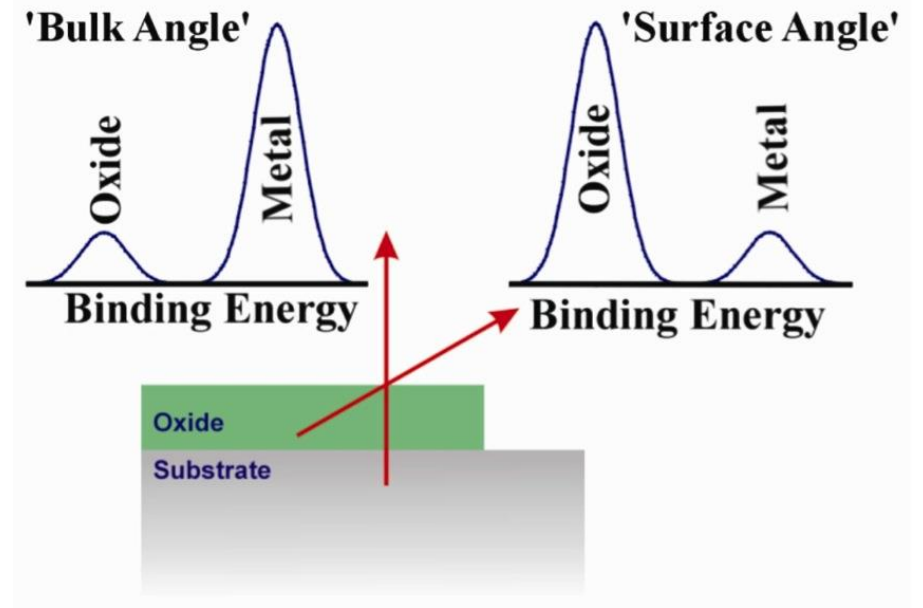
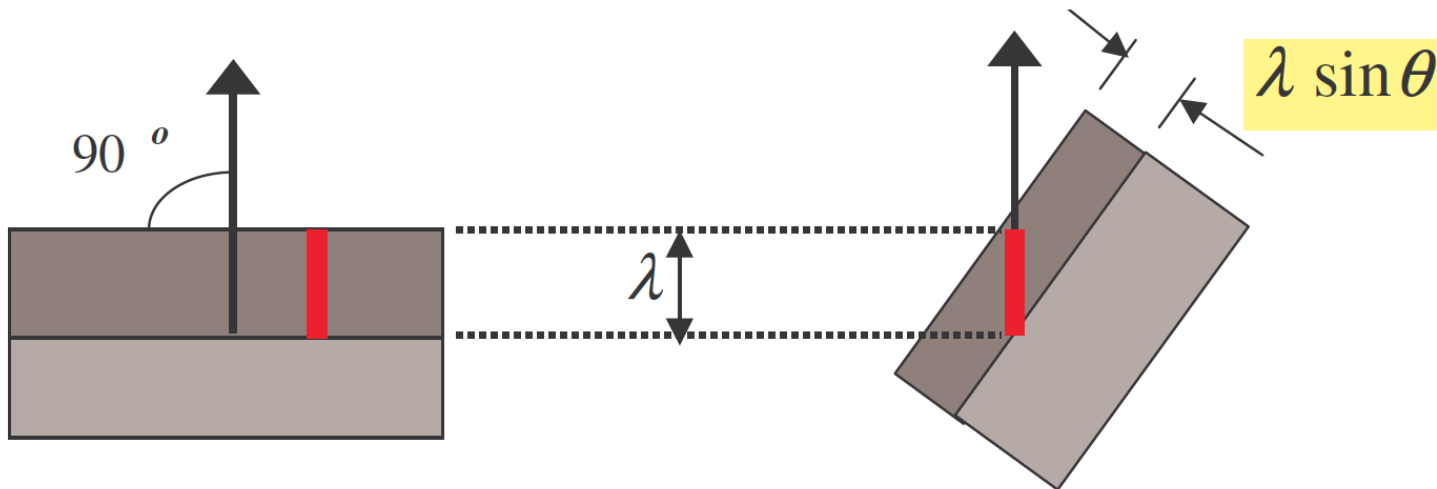
Energy from ion impacts can be distributed over a large volume in the sample



Angle resolved XPS

Alternative means for depth profiling:

- Consecutive XPS measurements are done while tilting the sample at increasing angles
- Escape depth for electrons decreases with increasing angle
- Higher surface sensitivity
- Reliable results only if surface is smooth enough!



Imaging methods

(1) Moving sample stage

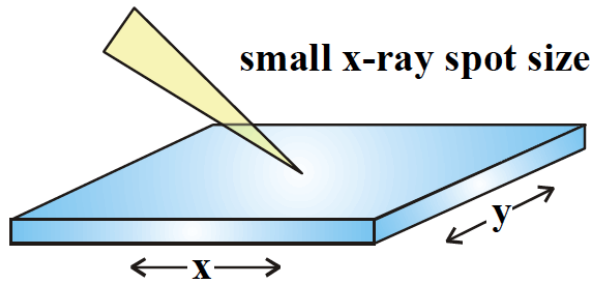


Image:

- Positions x and y scanned
- x, y -position vs photoelectron intensity
- Resolution: $\sim 50 \mu\text{m}$

(2) Use of scanning plates

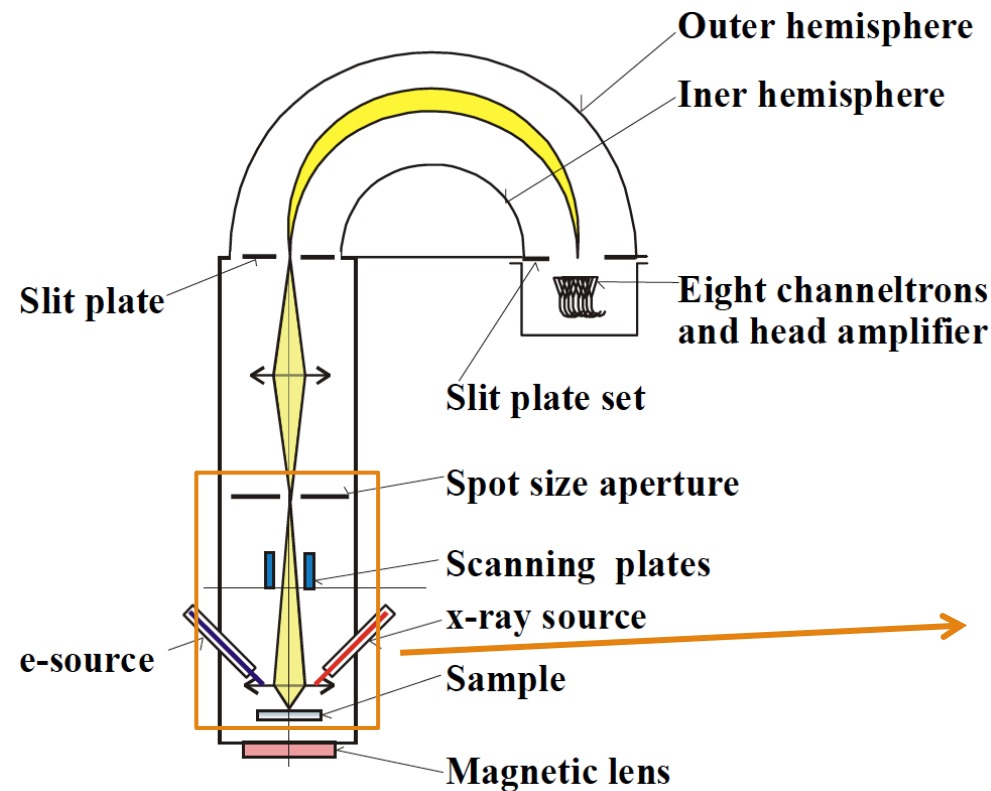
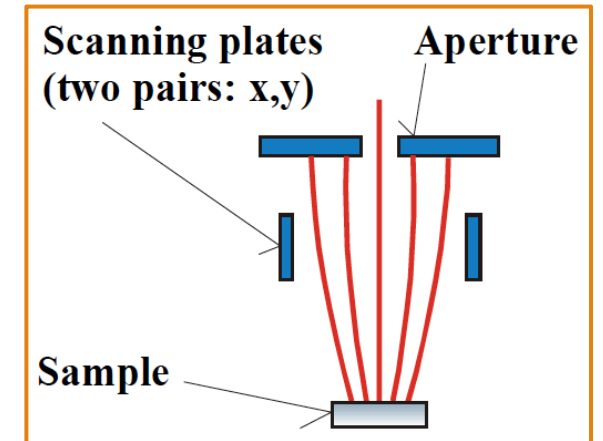
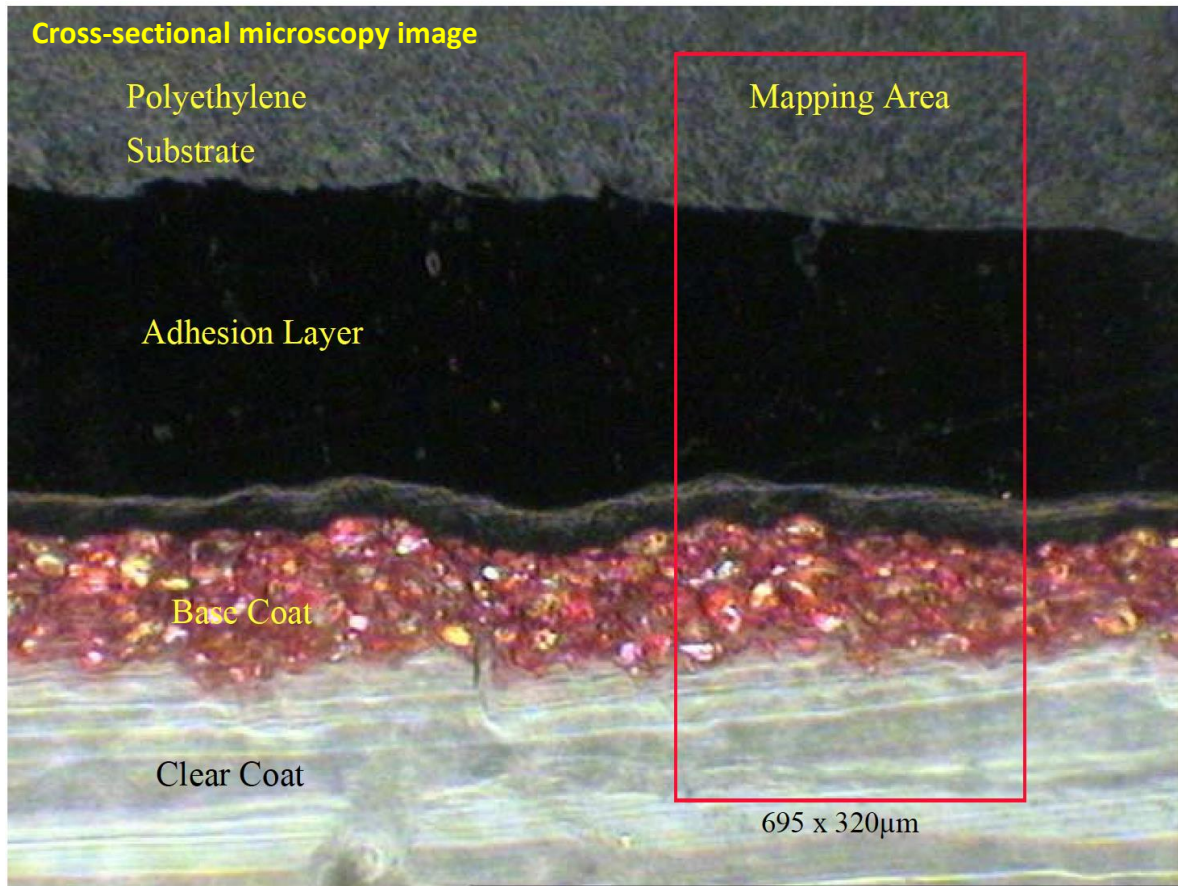


Image:

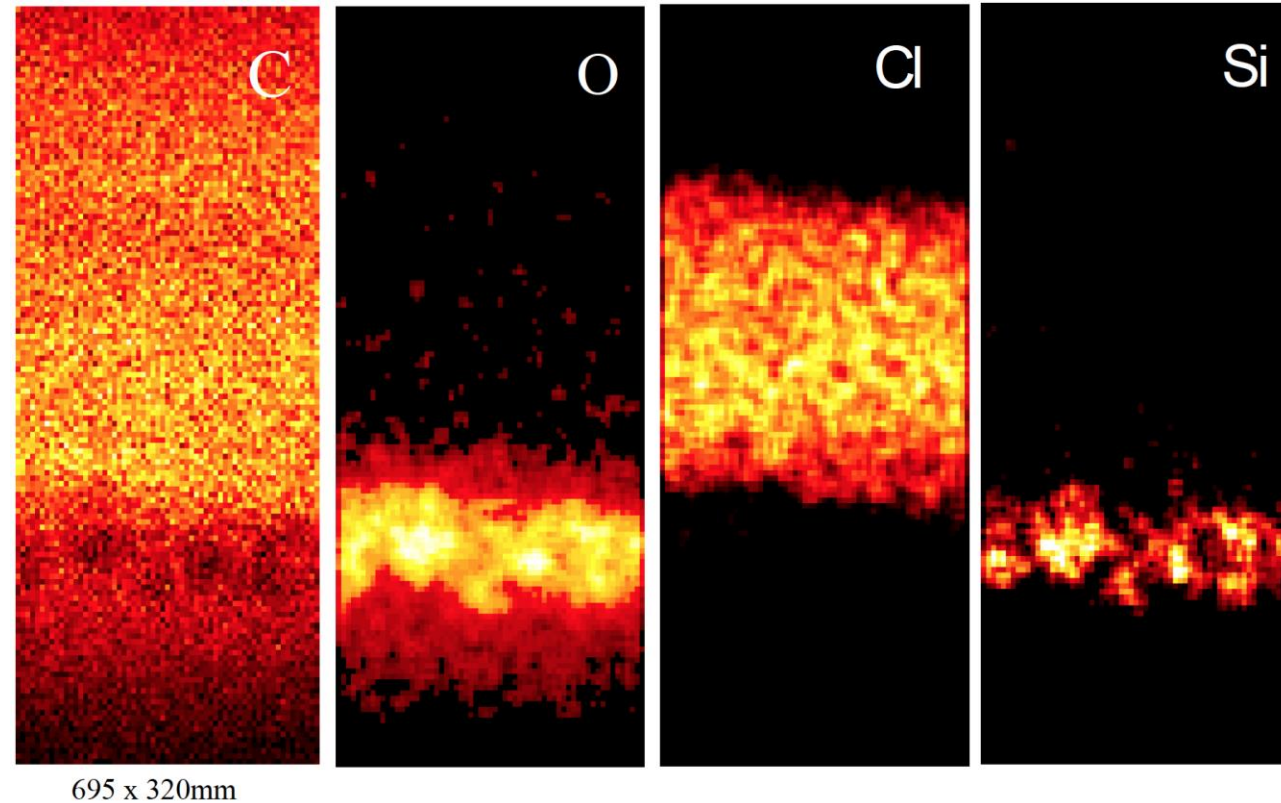
- Voltages V_x and V_y scanned
- Photoelectron intensity collected from different points in time sequence
- Resolution: $\sim 10 \mu\text{m}$



XPS study of paint

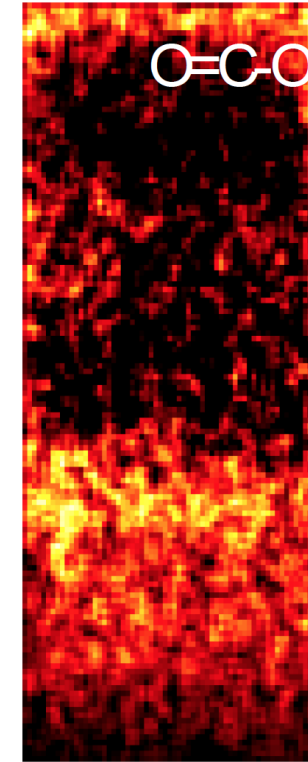
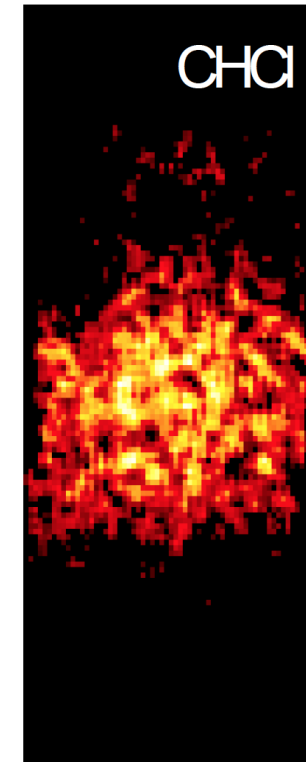
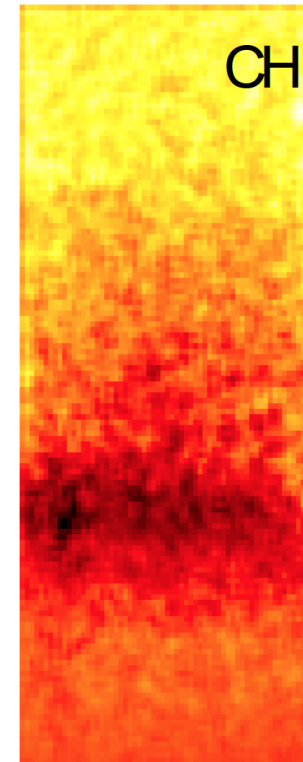
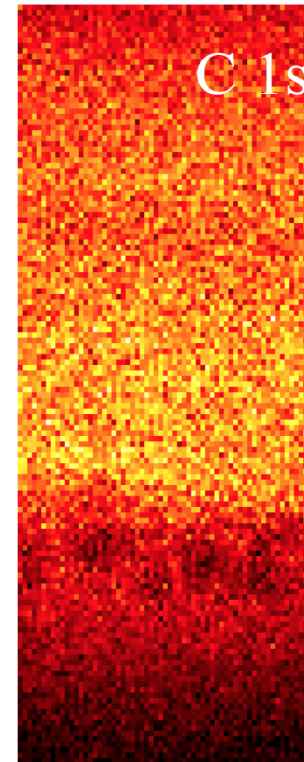
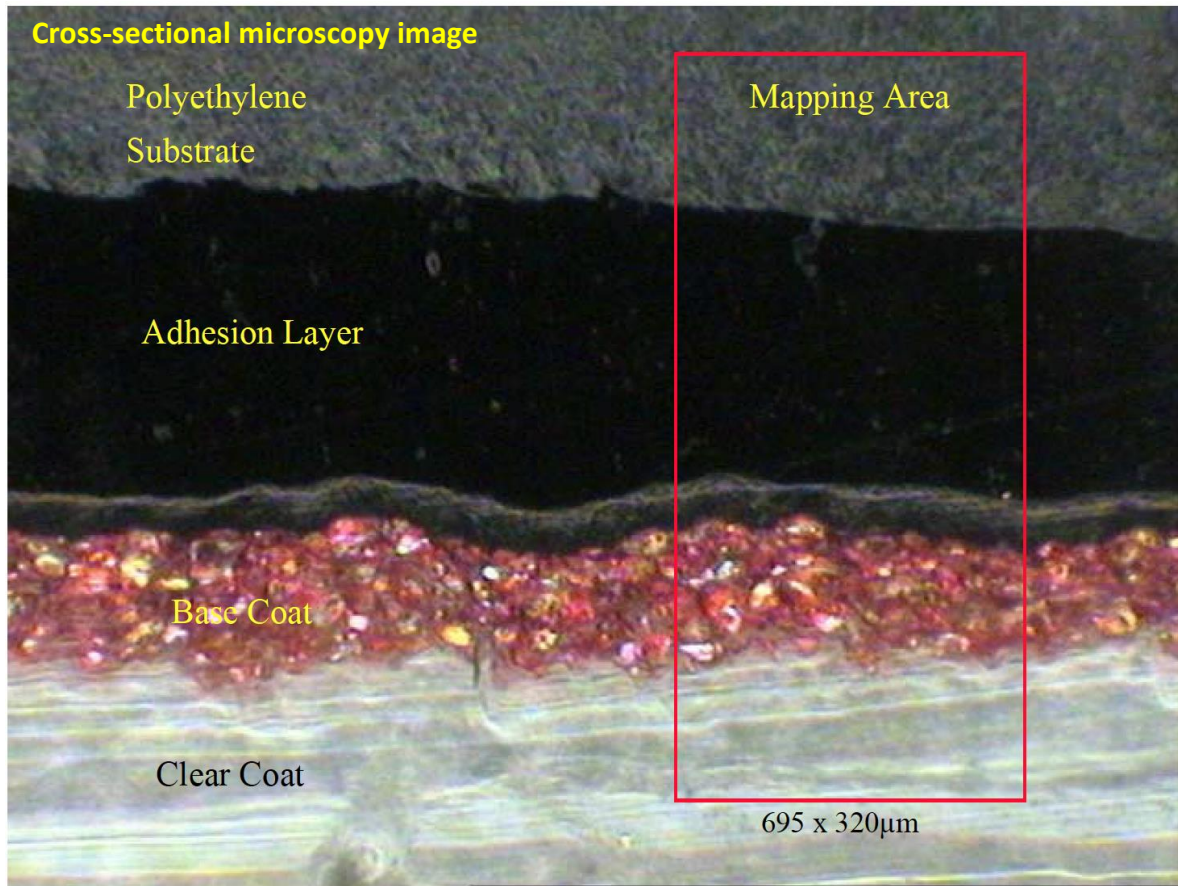


Elemental maps using C 1s, O 1s, Cl 2p, and Si 2p signals.



XPS study of paint – chemical state

C 1s chemical state maps.



Imaging methods

(3) Use of multichannel plate

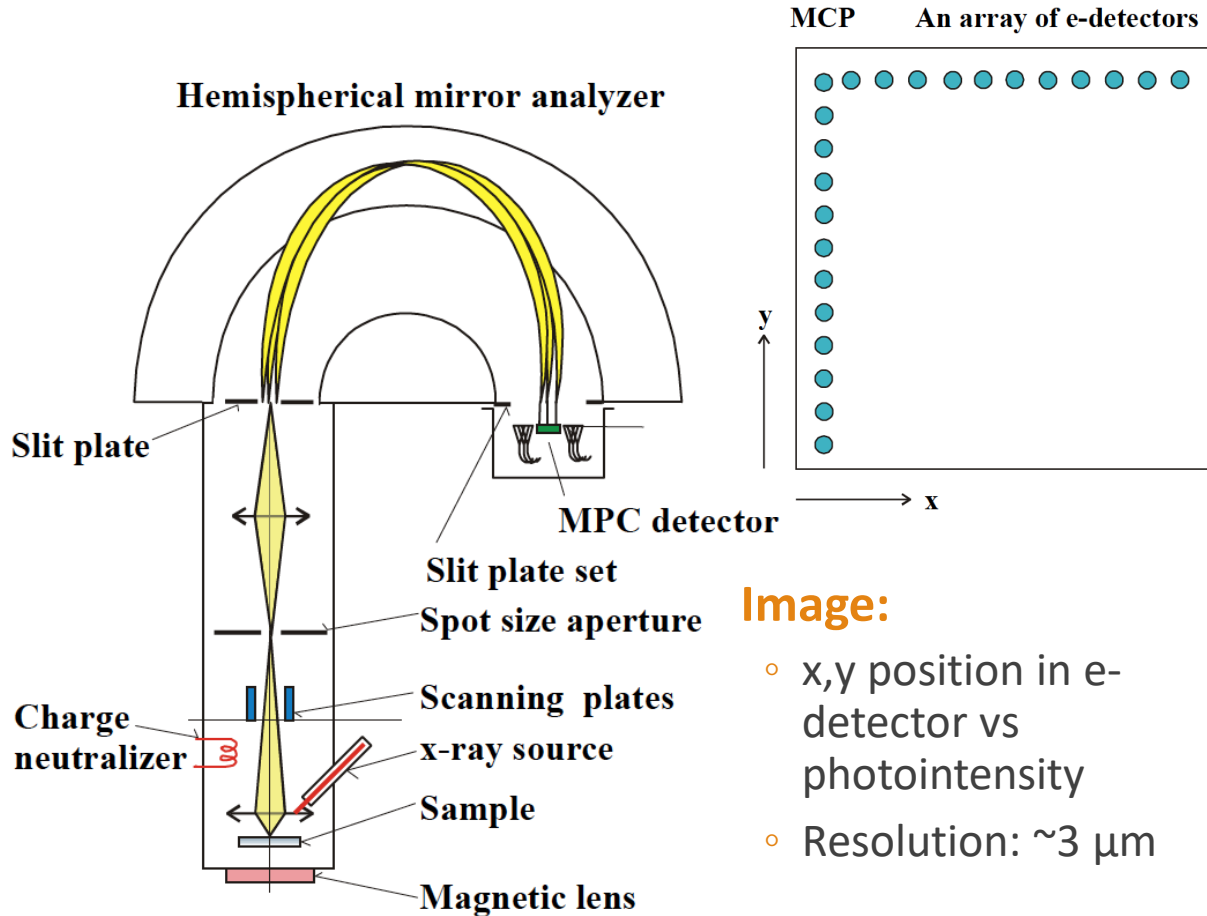
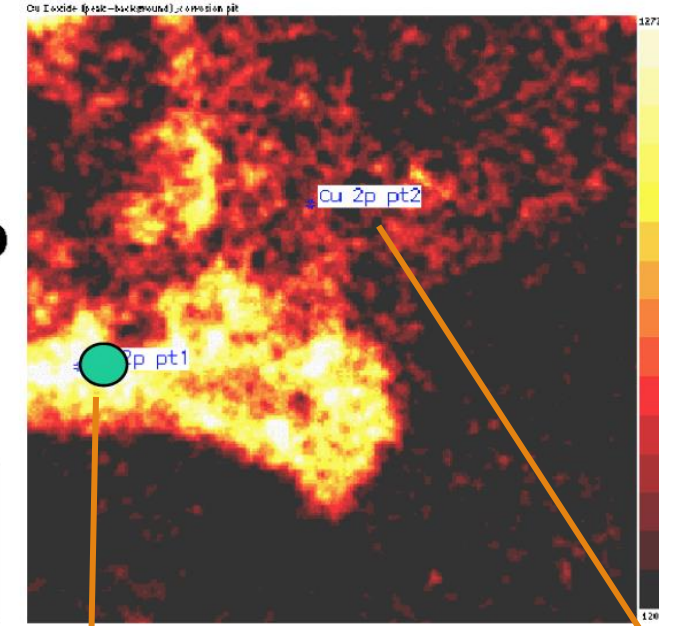


Image:

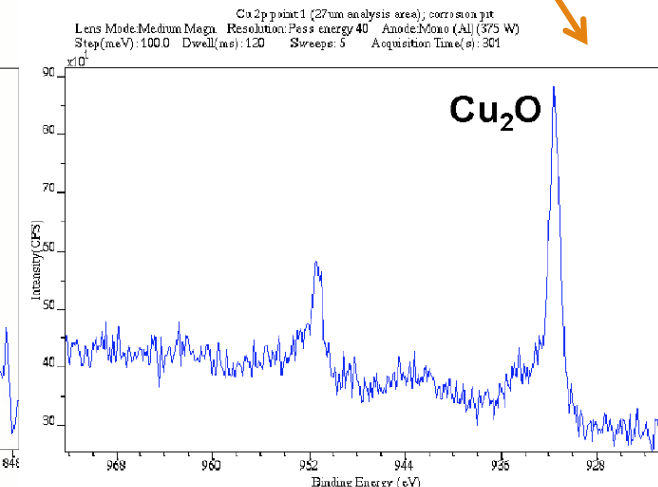
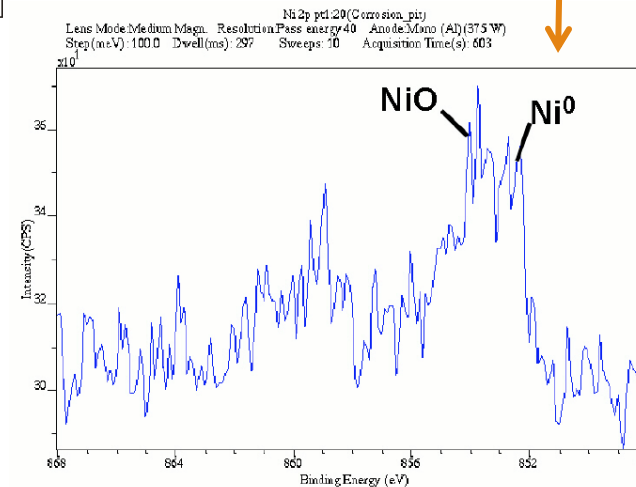
- x,y position in e-detector vs photointensity
- Resolution: $\sim 3 \mu\text{m}$

Cu₂O Map

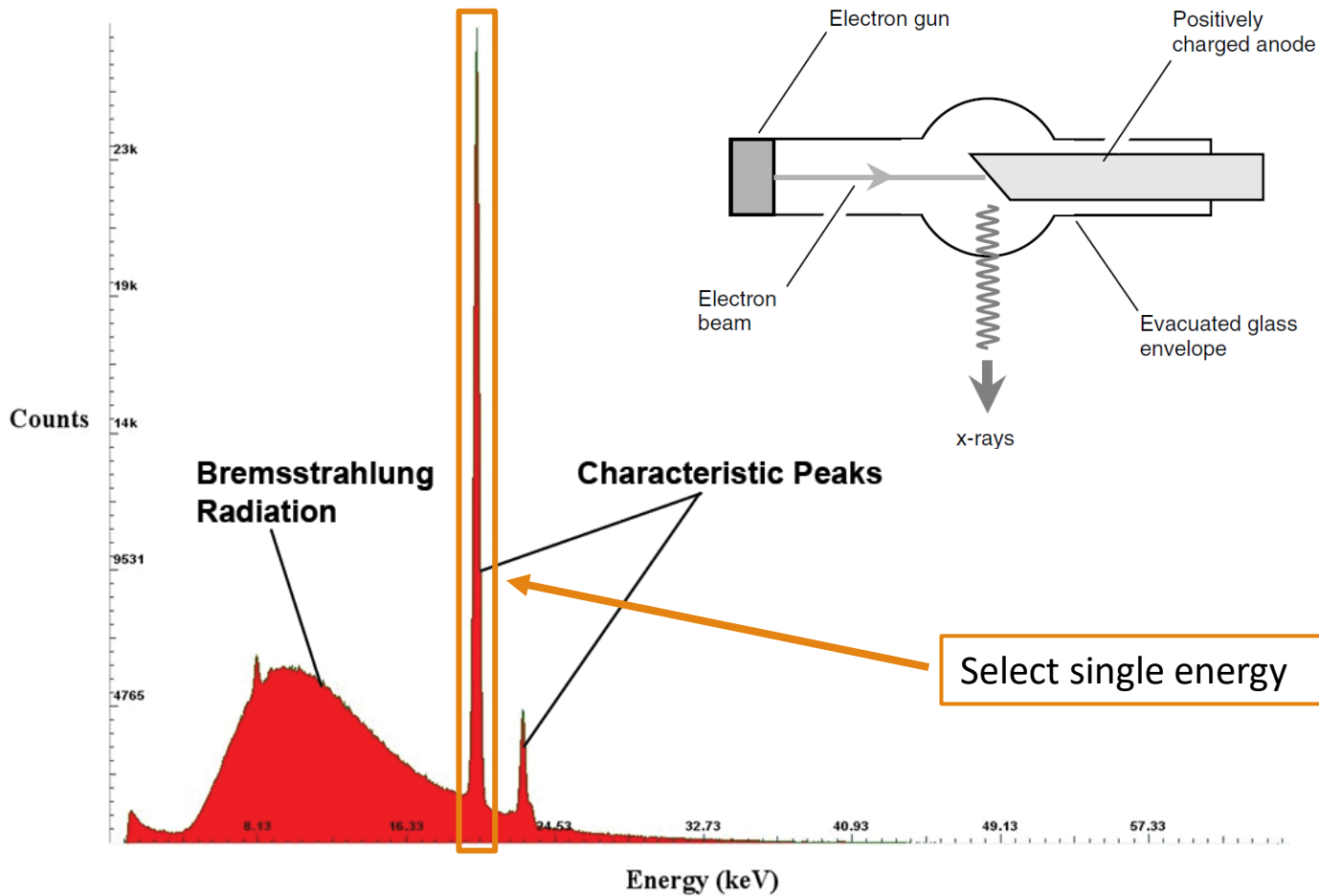
100 microns



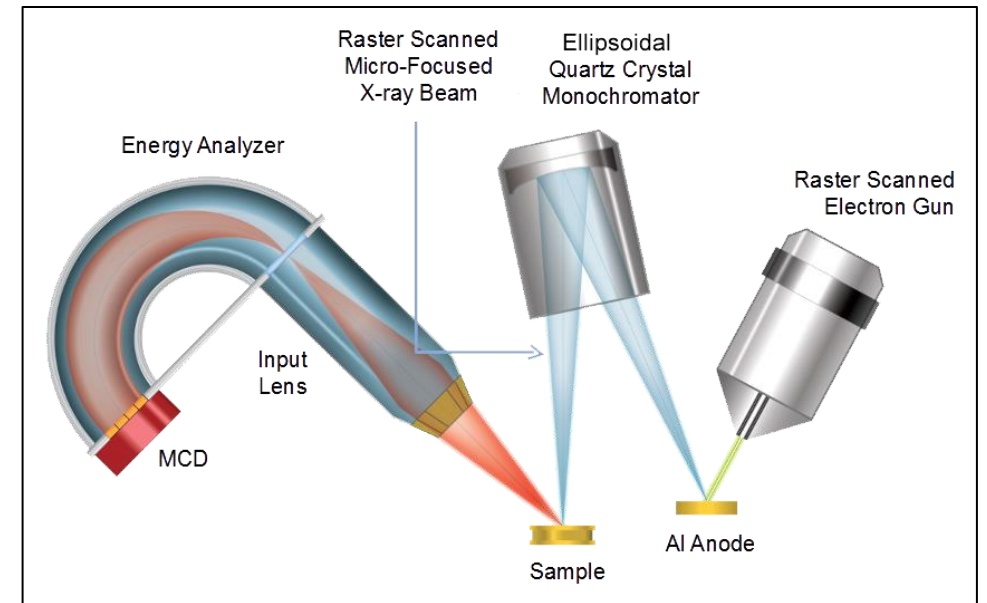
- Chemical state can be identified for each "spot" in image



X-Ray production



- X-ray tubes:
 - Continuous Bremsstrahlung
 - Characteristic peaks that depend on the anode material
- Unnecessarily large X-ray load & unwanted satellites in the spectra
- Solution: Monochromator



X-Ray monochromator

Advantages of X-monochromator:

- Narrow peak width, focusing of beam
- Reduced background, no satellite or ghost peaks

Disadvantage:

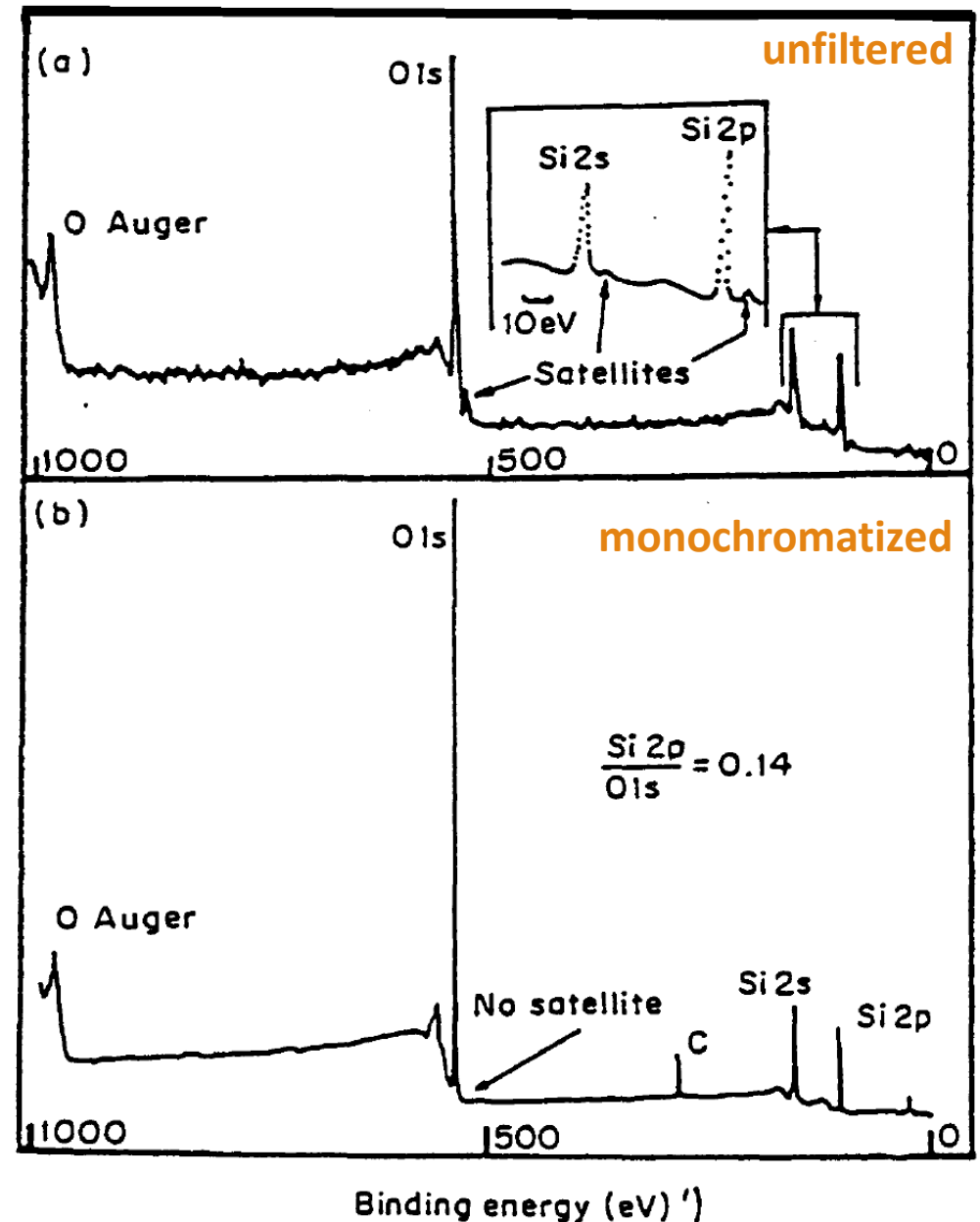
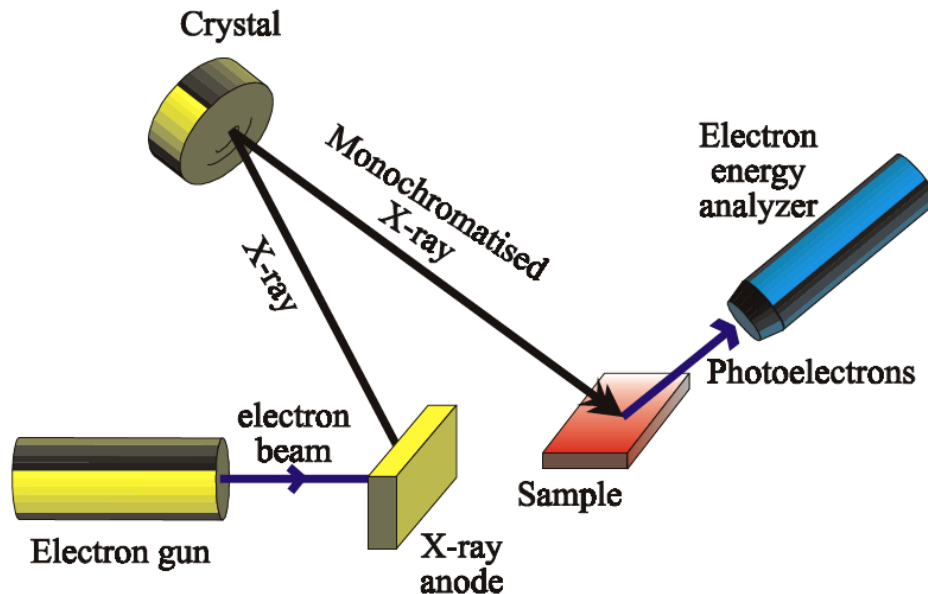
- 10-40 times lower intensity

Bragg diffraction:

$$n\lambda = 2d \sin \theta$$

For Al K_{α} :
 $\lambda = 8.3 \text{ \AA}$

Quartz ($10\bar{1}0$)
 planes:
 $d = 4.25 \text{ \AA}$
 $\theta = 78.5^{\circ}$



Synchrotron sources

- High intensity and resolution, energy tunability, polarization, pulsed beam, focused beam
- Big facilities: **high cost** – shared facilities

